

Specification and operation details of 100 nm & sub-10 nm focusing system at SACLA

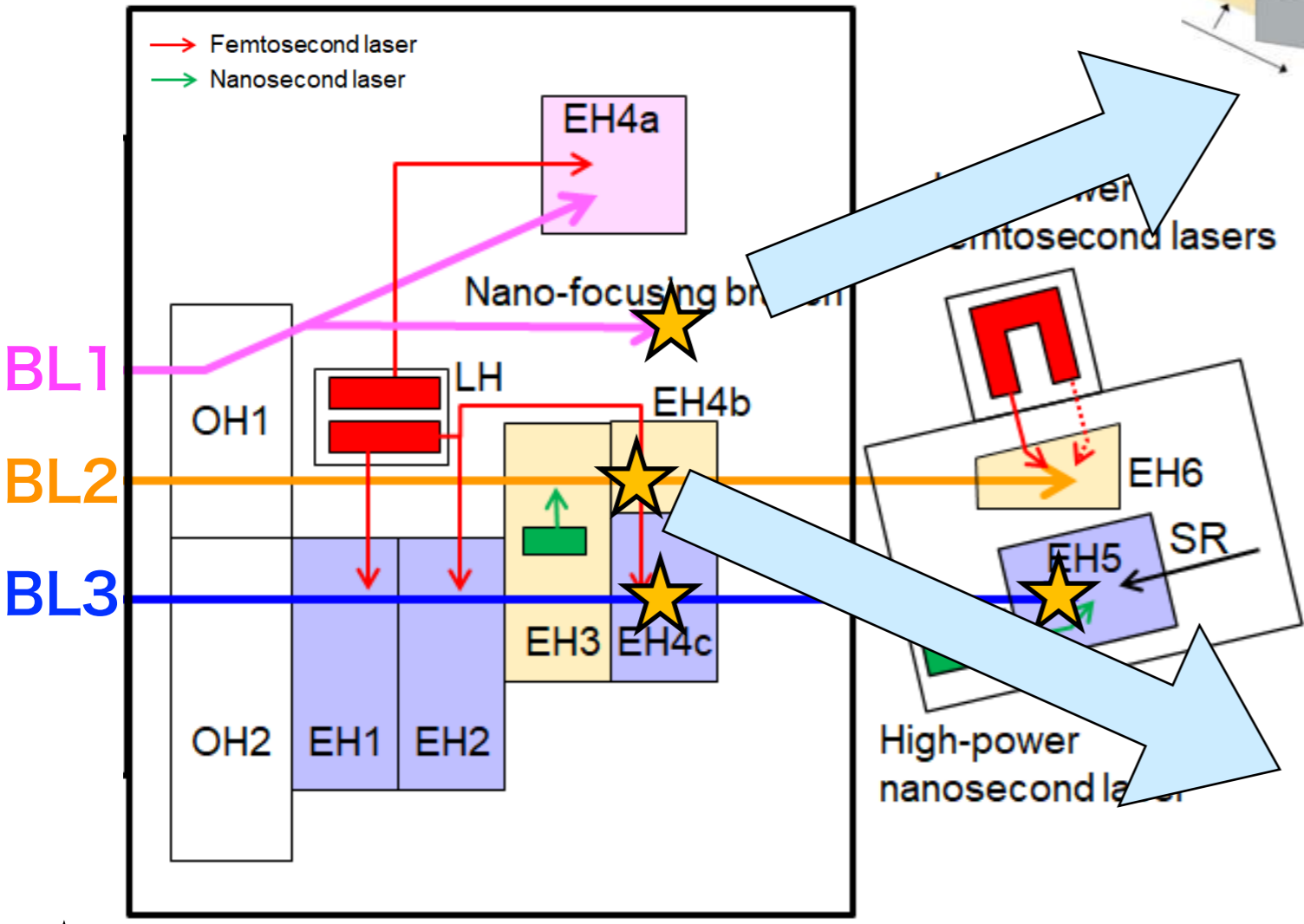
Jumpei Yamada (SACLA)





Nanofocusing system at SACLA

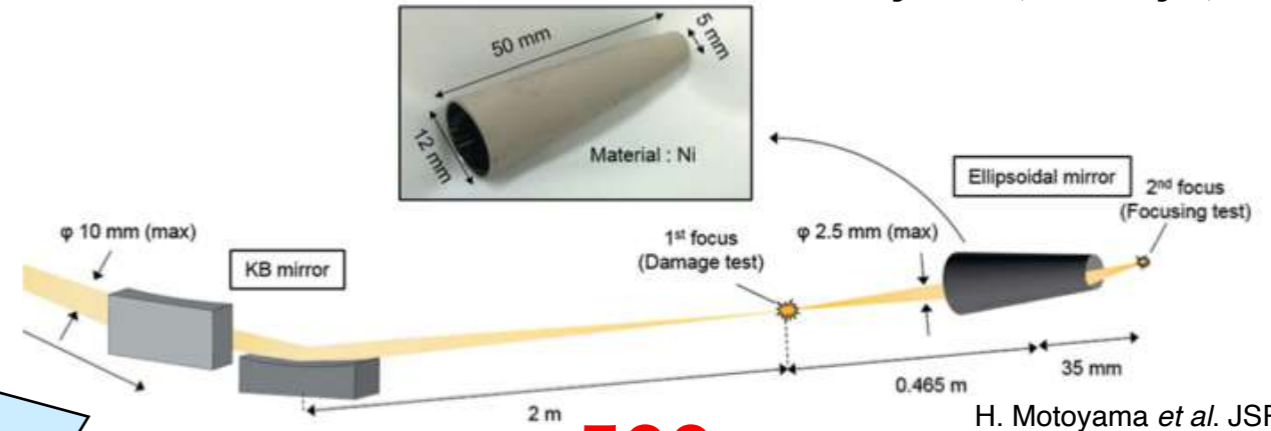
SACLA Experimental Facility



★ Nanofocusing system

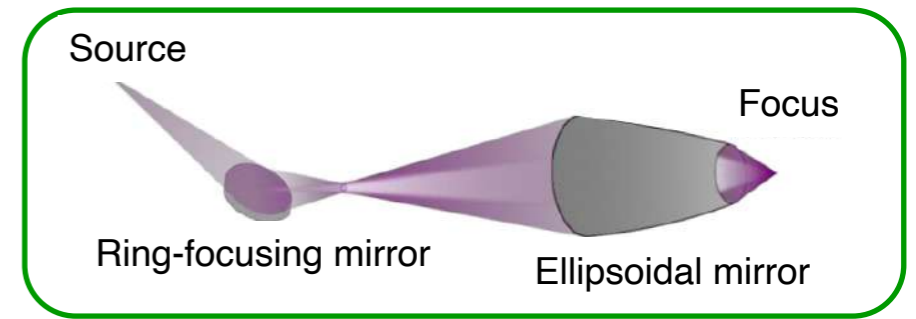
Soft X-ray nanofocusing

H. Mimura, H. Motoyama (U. Tokyo) *et al.*



H. Motoyama *et al.* JSR (2019)

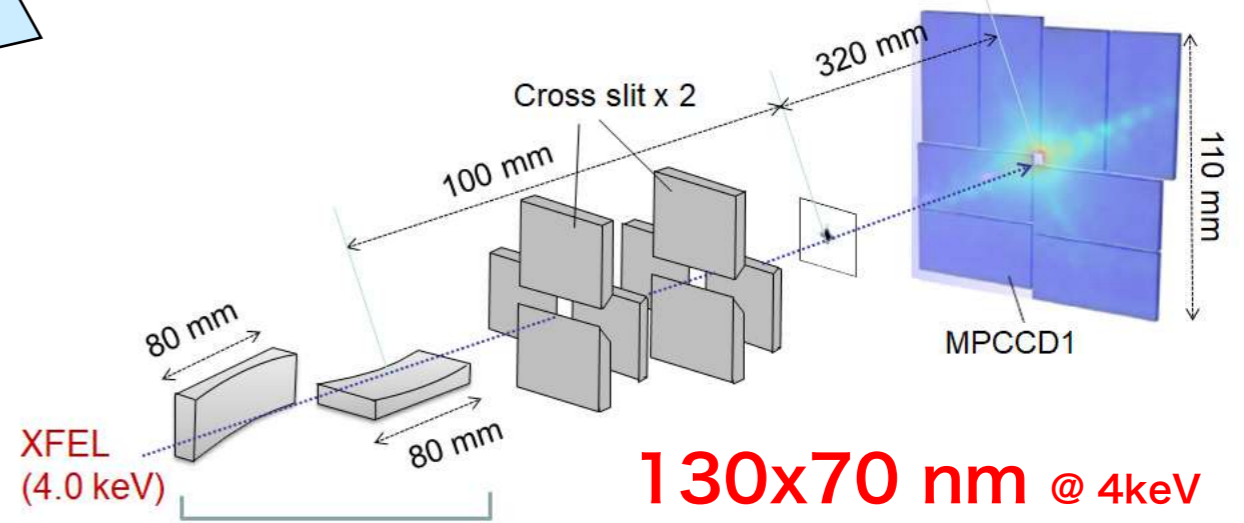
~500 nm @ 100-120eV



~50 nm @ 40-150eV is emerging

Nanofocusing for CDI (MAXIC-S)

H. Yumoto, T. Koyama, H. Ohashi (SACLA & SPring-8)
T. Kimura, A. Suzuki, Y. Nishino (Hokkaido U.), *et al.*

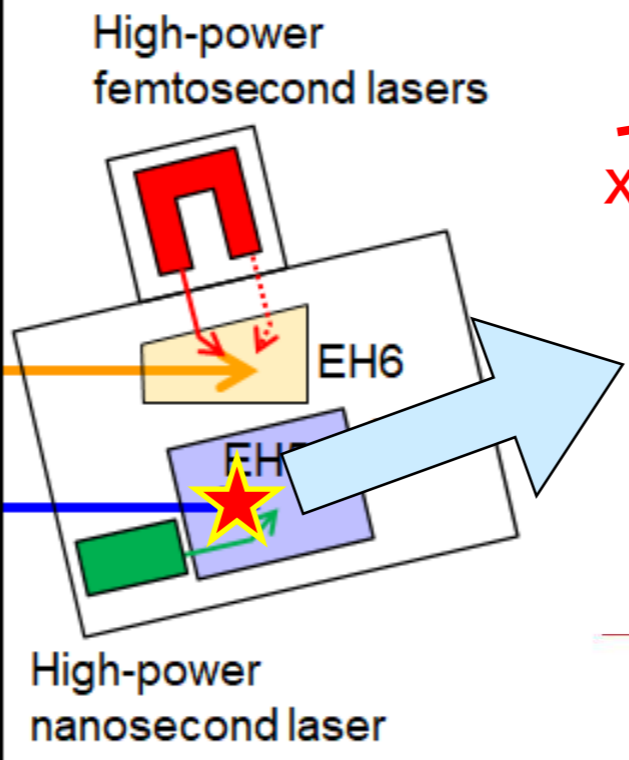
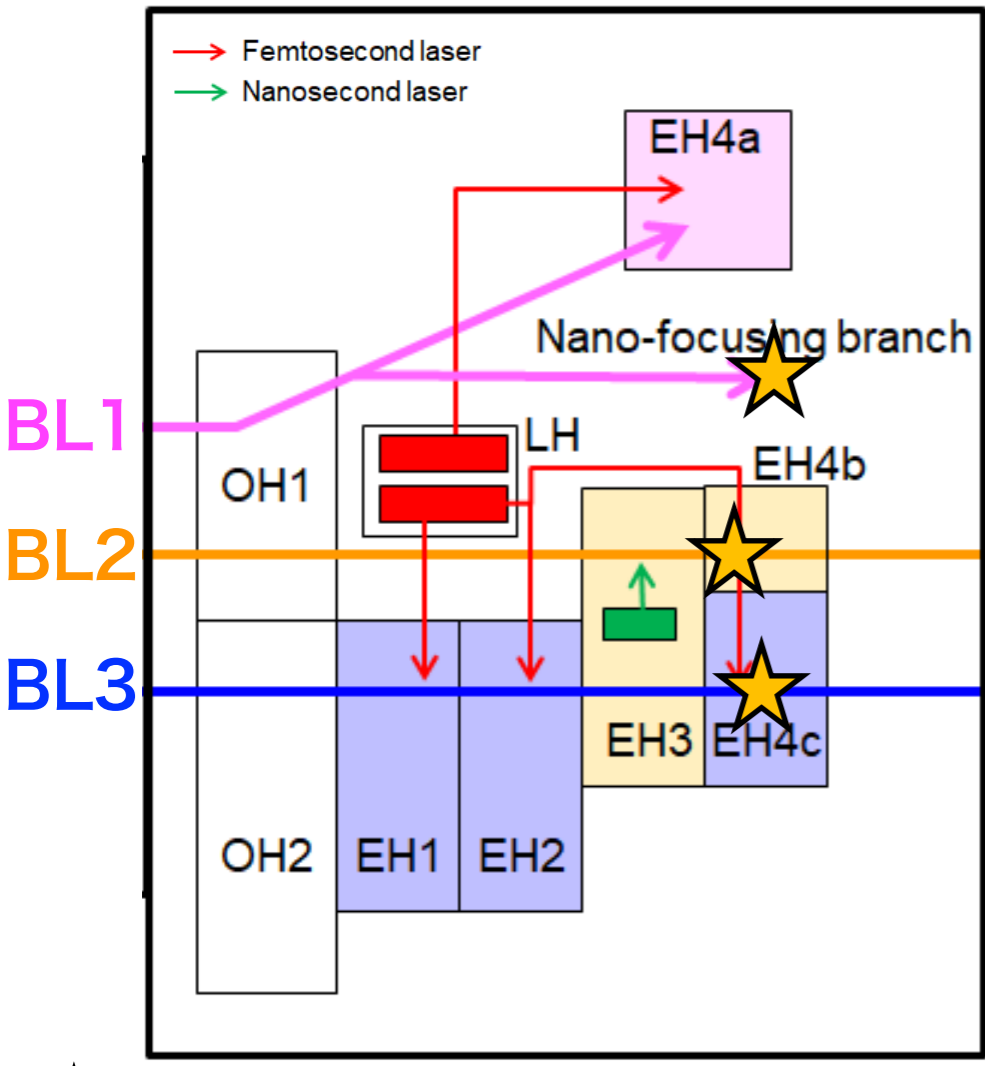


130x70 nm @ 4keV

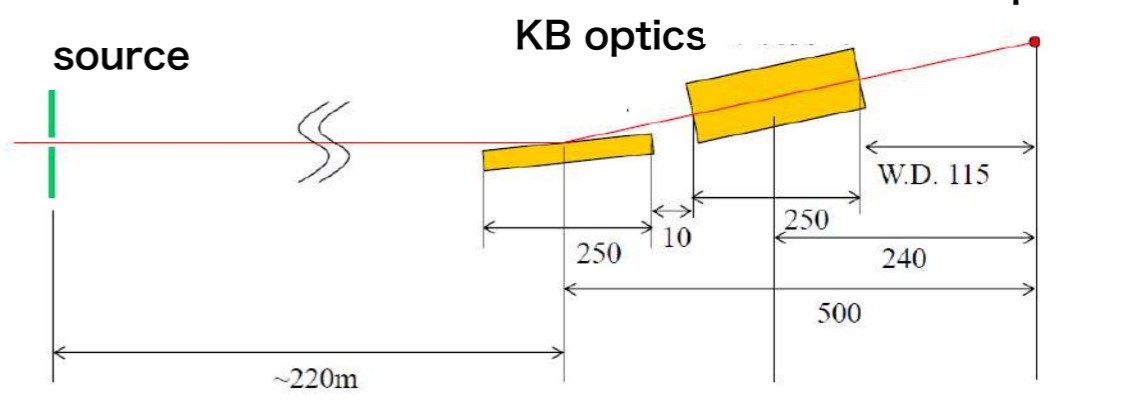
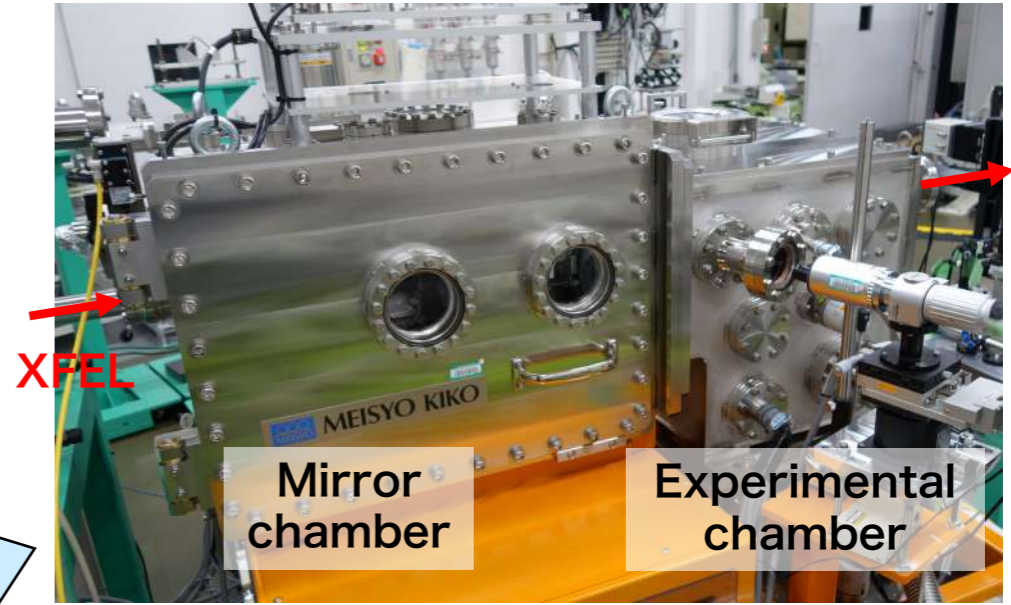


Topics 1: 100exa system

SACLA Experimental Facility



100-200 nm focusing @ 6-12keV (100exa)



★ Nanofocusing system

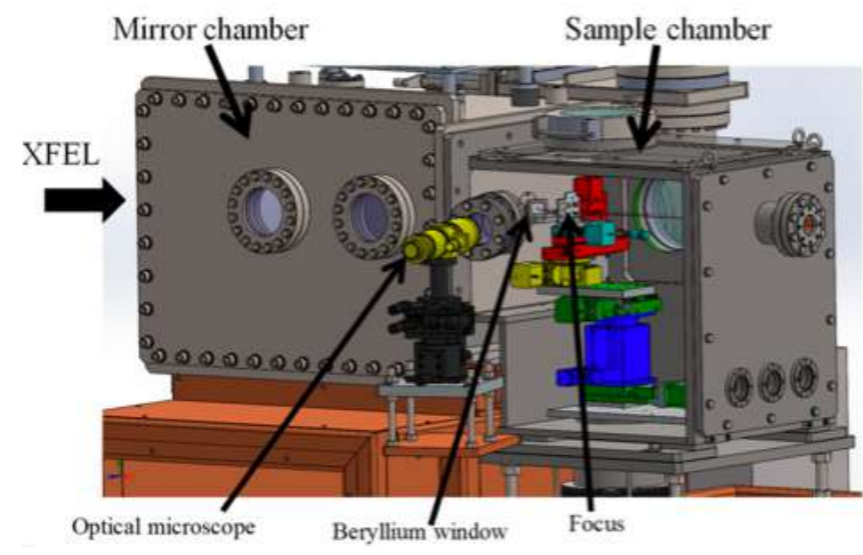


100exa focusing system

XFEL 100-200 nm focusing with 10^{20} W/cm² (= **100EW/cm²**)



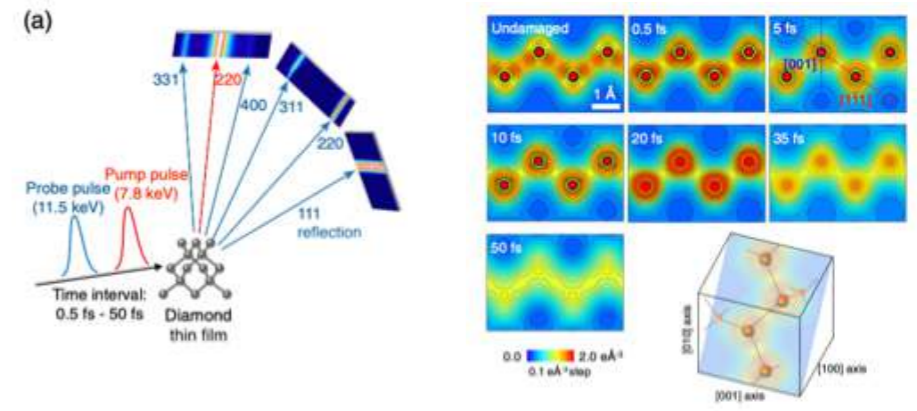
Drs. Ohashi-san, Yumoto-san (JASRI)



PHYSICAL REVIEW LETTERS 126, 117403 (2021)

Atomic-Scale Visualization of Ultrafast Bond Breaking in X-Ray-Excited Diamond

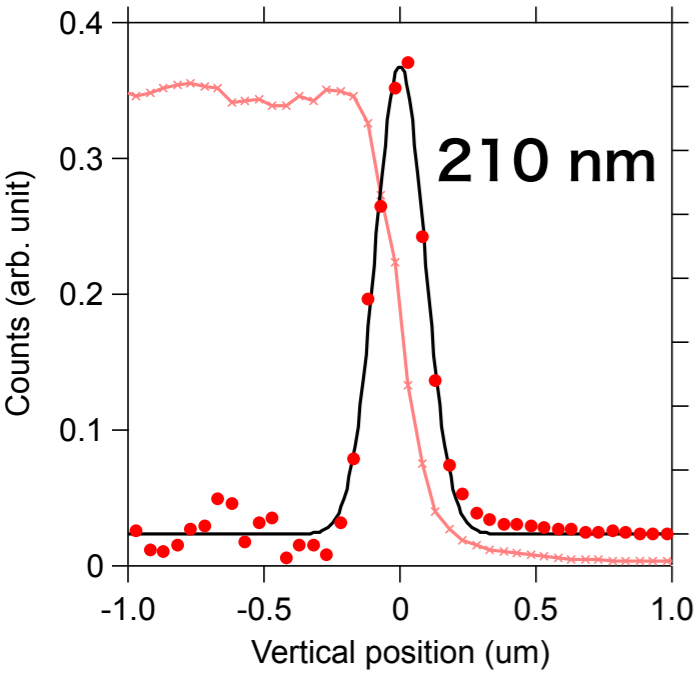
Ichiro Inoue,^{1,*,†} Yuka Deguchi,^{2,†} Beata Ziaja,^{3,4,†} Taito Osaka,¹ Malik M. Abdullah,³ Zoltan Jurek,³ Nikita Medvedev,^{5,6} Victor Tkachenko,^{4,7,3} Yuichi Inubushi,^{8,†} Hidetaka Kasai,^{2,9} Kenji Tamasaku,¹ Toru Hara,¹ Eiji Nishibori,^{2,9,†} and Makina Yabashi^{1,8}



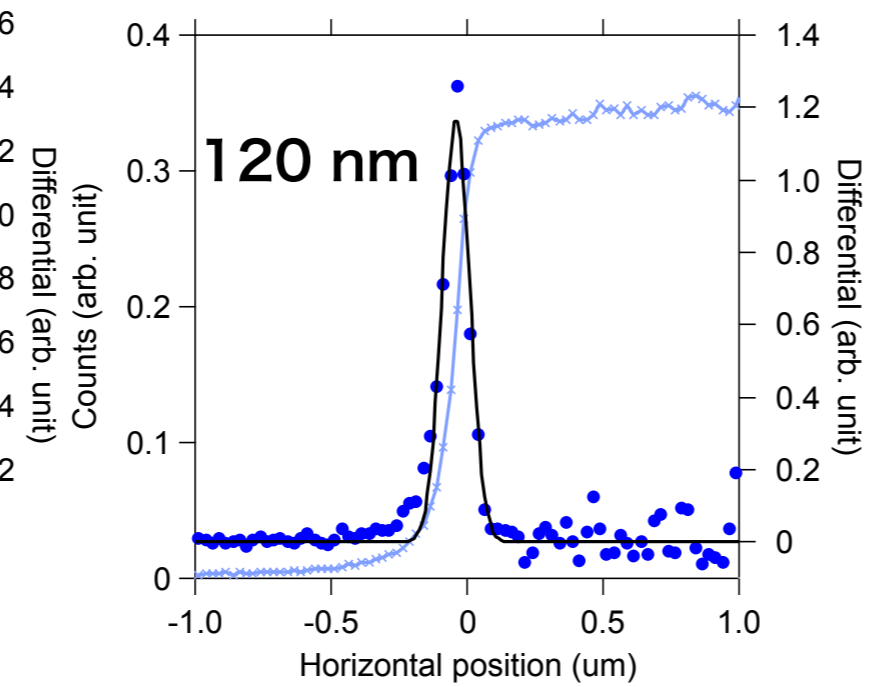
I. Inoue *et al.*, PRL 126 (2021)

Focus size

Vertical



Horizontal

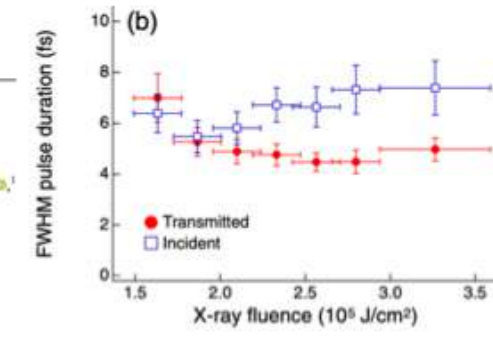


H. Yumoto *et al.*, Appl. Sci. (2020)

PHYSICAL REVIEW LETTERS 127, 163903 (2021)

Shortening X-Ray Pulse Duration via Saturable Absorption

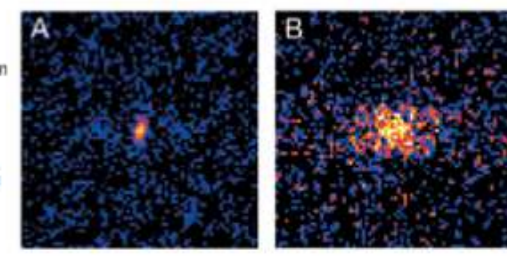
Ichiro Inoue,^{1,*} Yuichi Inubushi,^{1,2} Taito Osaka,¹ Junpei Yamada,¹ Kenji Tamasaku,¹ Hitoki Yoneda,³ and Makina Yabashi^{1,2}



I. Inoue *et al.*, PRL 127 (2021)

Focus characterization of an X-ray free-electron laser by intensity correlation measurement of X-ray fluorescence

Nami Nakamura,² Satoshi Matsuyama,^{2*} Takato Inoue,² Ichiro Inoue,³ Junpei Yamada,^{4,5} Taito Osaka,^{4,5} Makina Yabashi,³ Tetsuya Ishikawa³ and Kazuo Yamauchi²



N. Nakamura *et al.*, JSR 27 (2020)



100exa focusing system

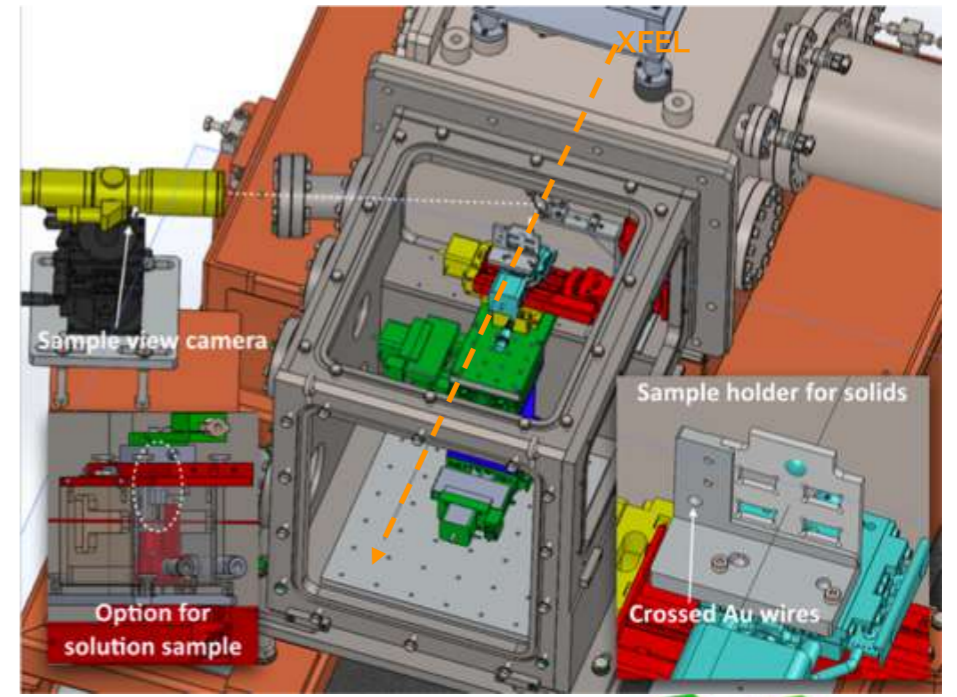
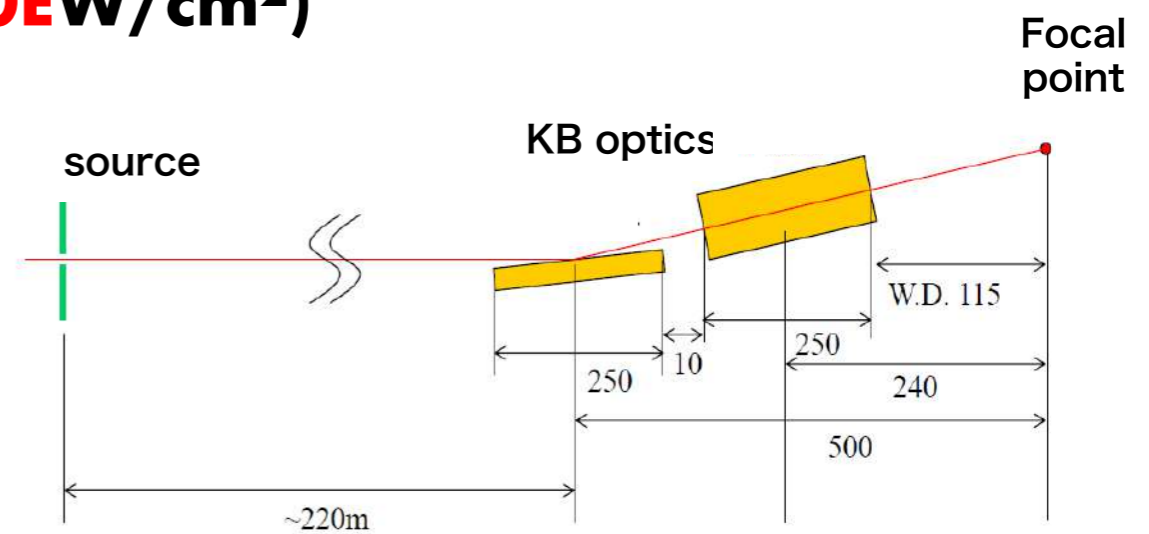
XFEL 100-200 nm focusing with 10^{20} W/cm^2 (= **100EW/cm²**)

Specification

- Photon energy : <12 keV
- Reflectivity: >80 % @ 12keV
- Acceptance: ~1 x 1 mm (cf. incident ~550 um fwhm)
- Throughput: >25% (including all BL-optics)
- Sample type: Solid (foil), liquid jet, gas, etc.

- Focus size: ~100 nm x ~200 nm
- Depth of focus: ~65 um

- Tuning time: 4~5 hours (initial tuning)
2~3 hours (re-focusing)
- Lifetime of focus: **~12 hours**



Issues

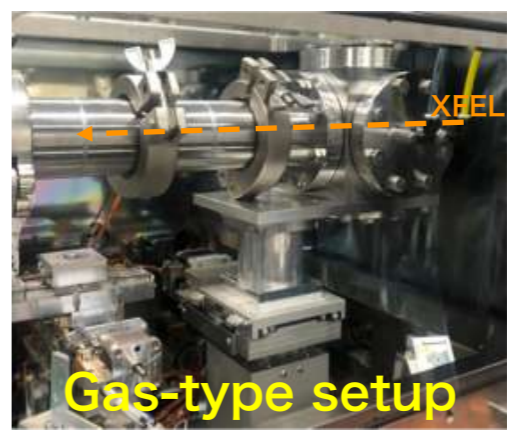
The measurements have been restricted by re-focusing

└ ~3h of interruption every 10~12h.

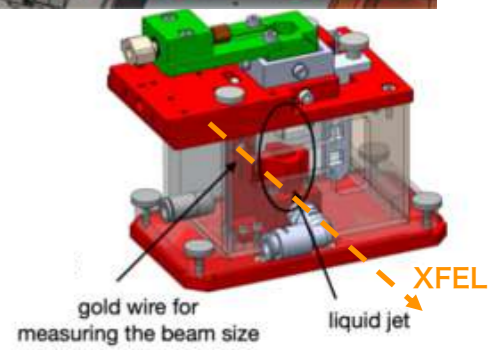
Re-focusing was just try-errors of wire-scanning

└ Less quantitative

└ (BL staffs were exhausted...)



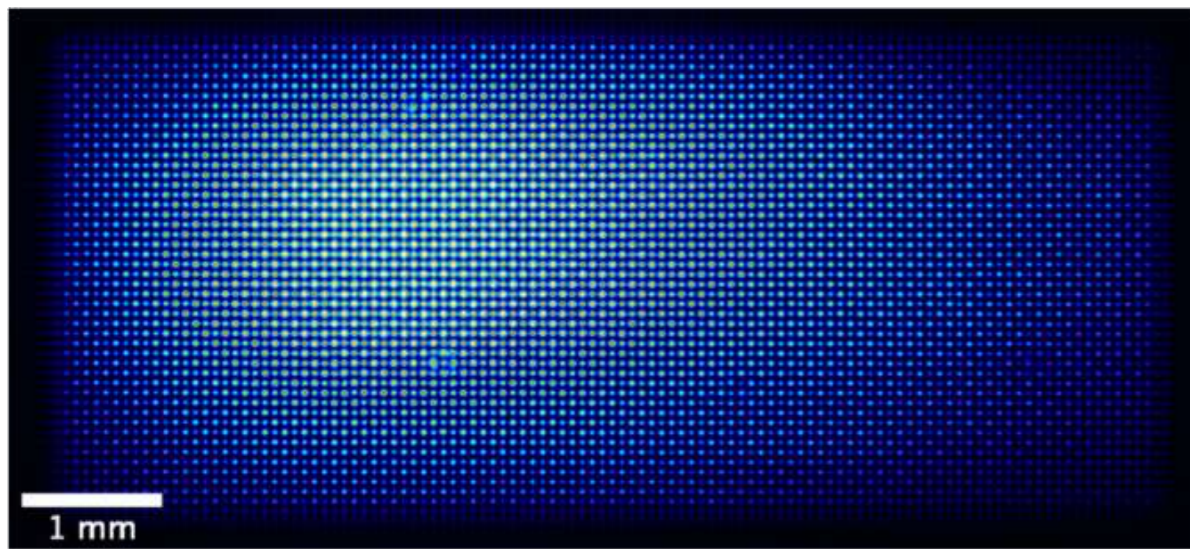
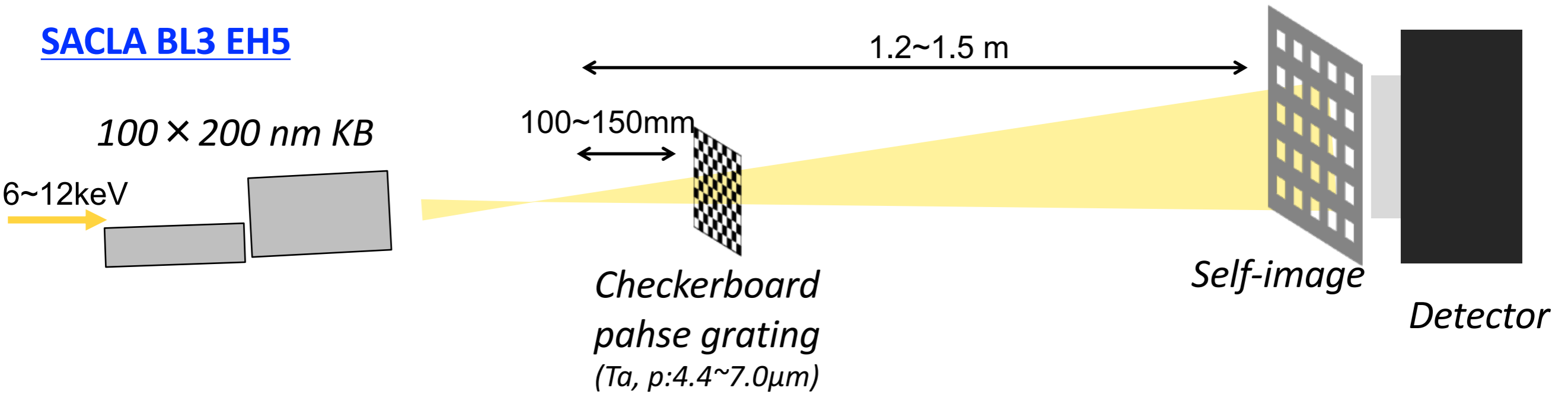
Gas-type setup



Liquid-type setup

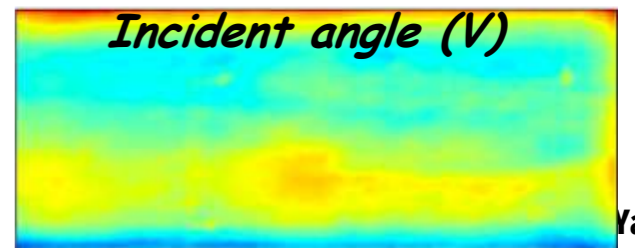
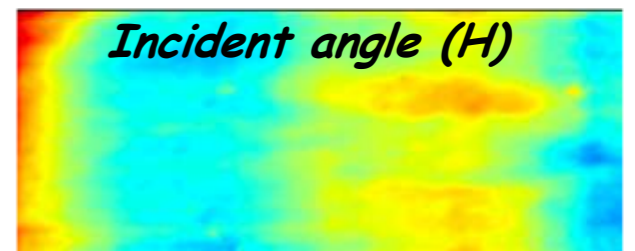
Automated optimization of 100exa: nanofocusing KB via wavefront measurement

SACLA BL3 EH5



Typical self-image

FFT analysis
&
Cosine transform integration



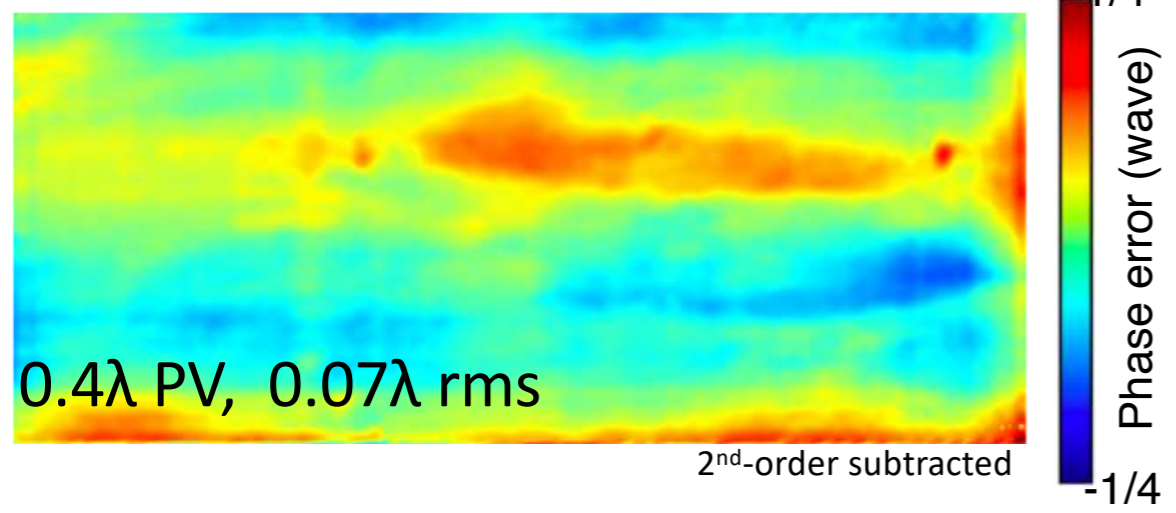
- ☑ Relatively compatible setup with user's experiments.
- ☑ Fast and less-chromatic wavefront measurement.
- ☑ Quantification of KB alignment errors.



Automated optimization of 100exa: nanofocusing KB via wavefront measurement

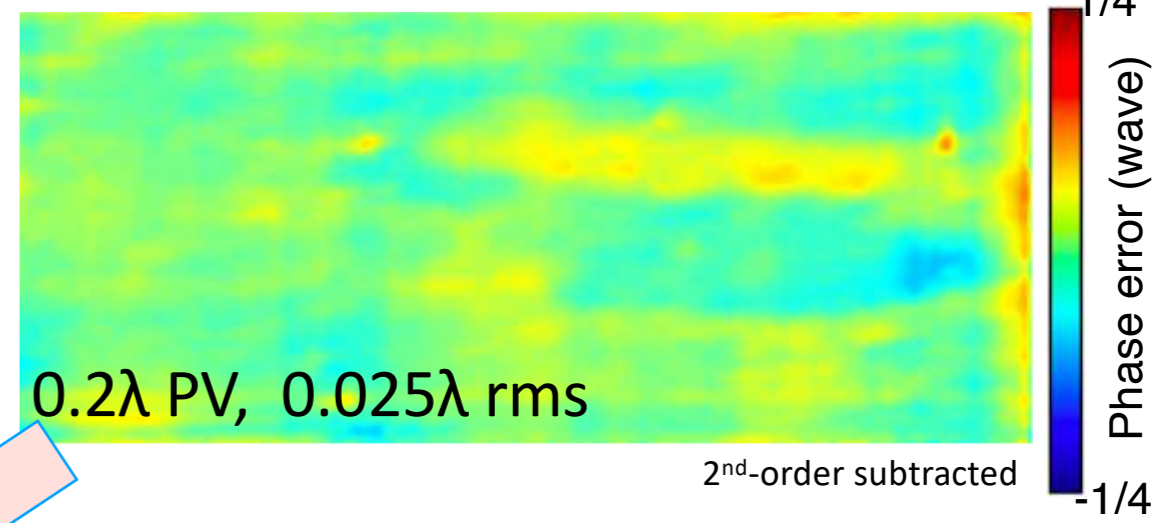
Performance Test @ 9.07 keV SASE

10 hours after the tuning



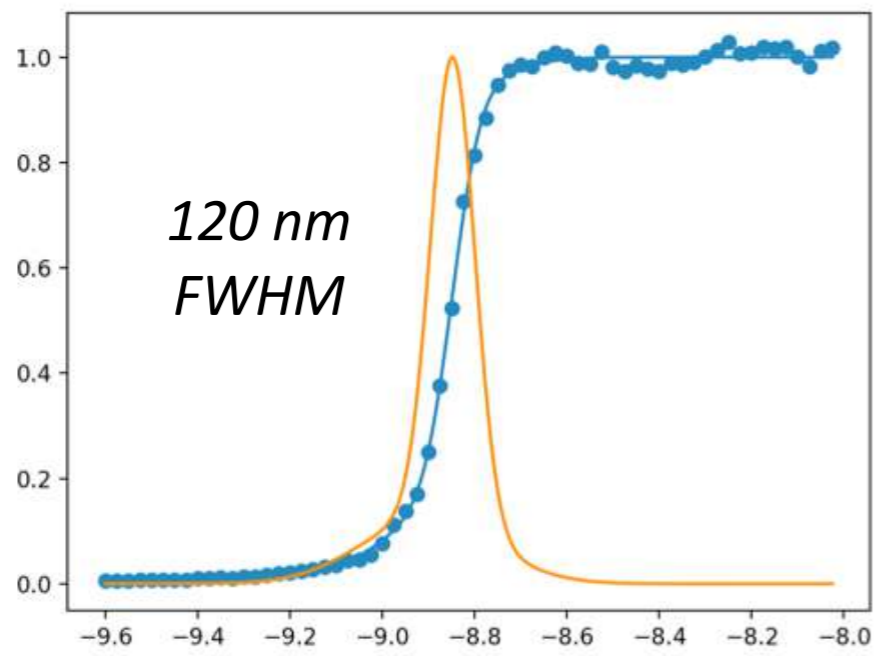
<10 min.
Auto-tuning

Result of re-tuning

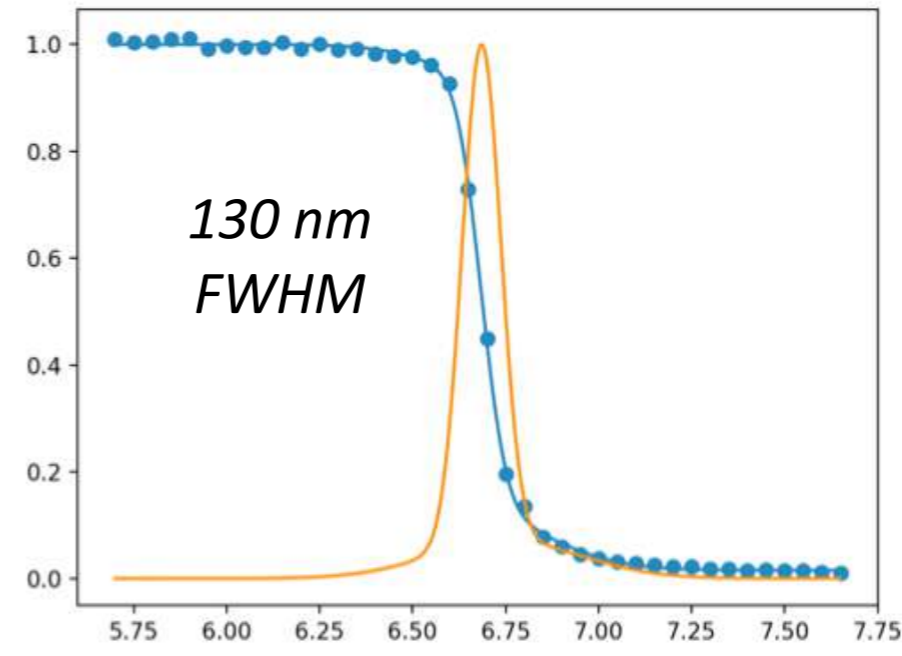


Cross-check with wire (knife-edge) scan

Horizontal



Vertical



- ☑ 2~10 min auto-refocusing is available by users themselves.
- ☑ The wavefront was consistent with the knife-edge scan.



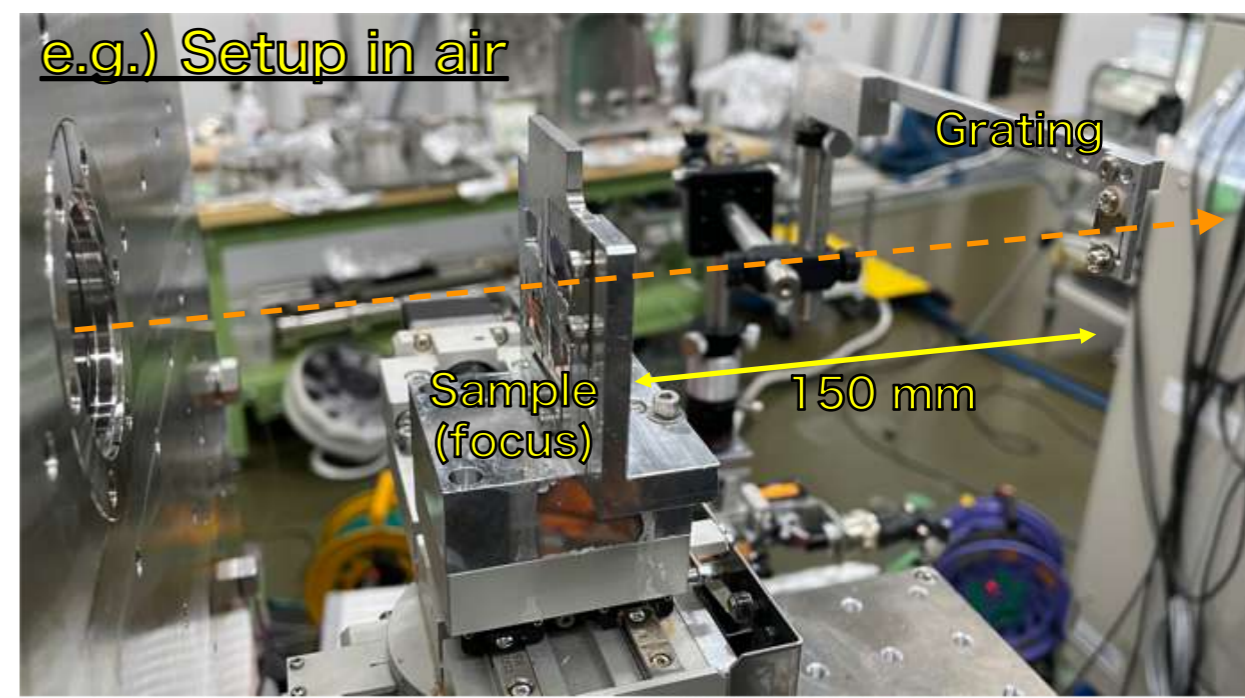
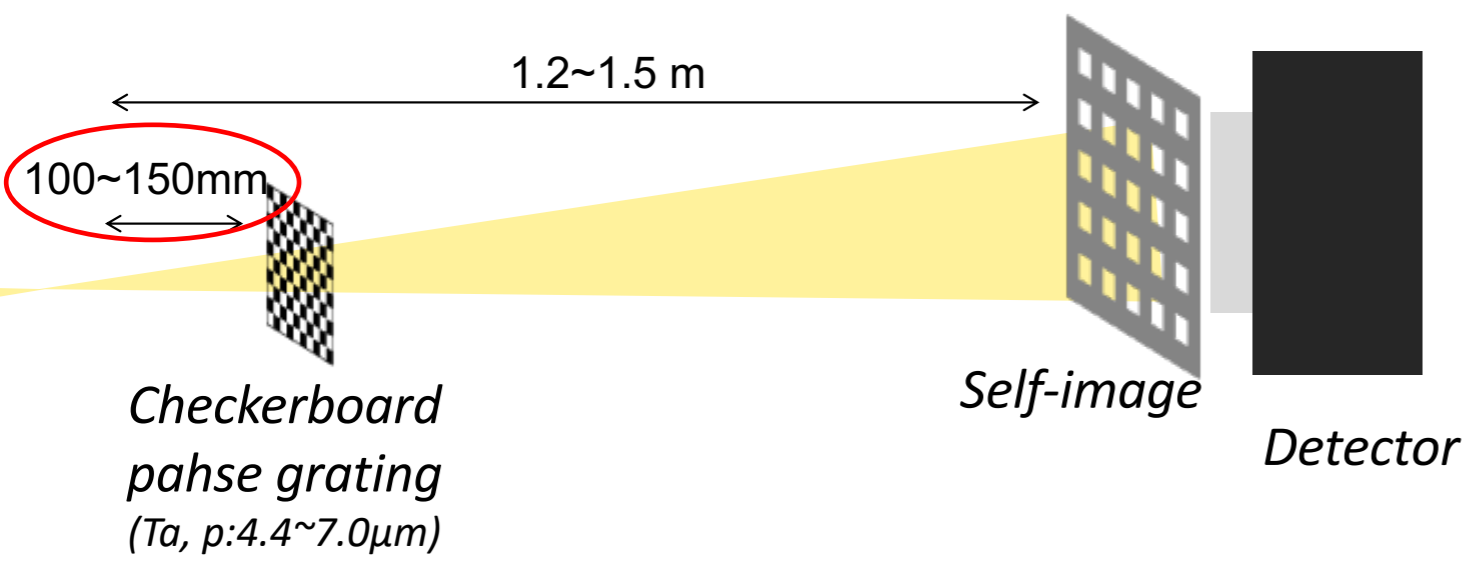
Topics 1: 100exa system

From SACLA side:

We recommend to use the grating-based auto-tuning system.

If acceptable, convenient & effective nanofocused XFEL will be available.

Requirement: Make space for the grating



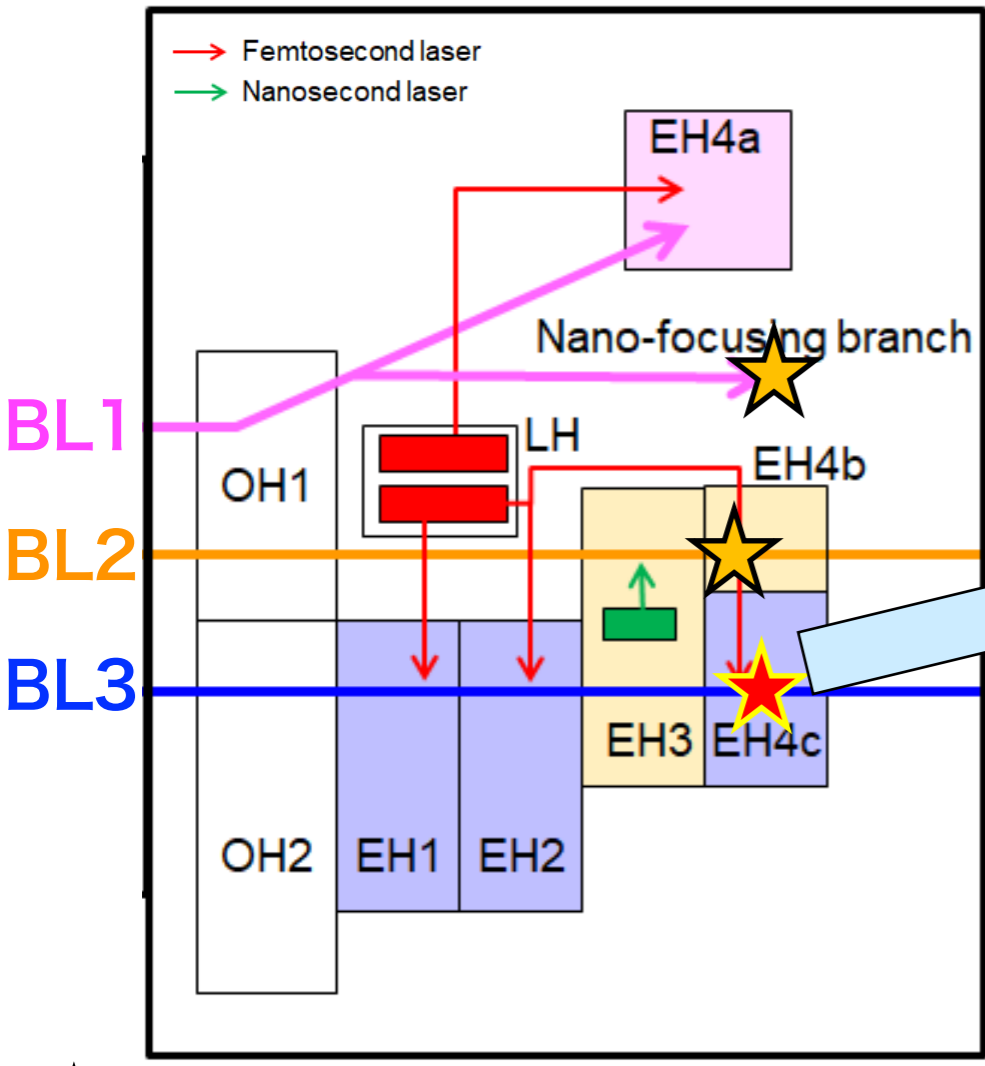
Photon Energy	5.50	5.75	6.00	6.25	6.50	6.75	7.00	7.25	7.50	7.75	8.00	8.25	8.50	8.75	9.00	9.25	9.50	9.75	10.00	10.25	10.50	10.75	11.00	11.25	11.50	11.75	12.00
Grating1: 4.4µm								5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8	5/8
Grating2: 7µm					3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8	3/8
Grating3: 6.4µm	5/8	5/8	5/8	5/8	5/8																						

5/8 Talbot order
 3/8 Talbot order

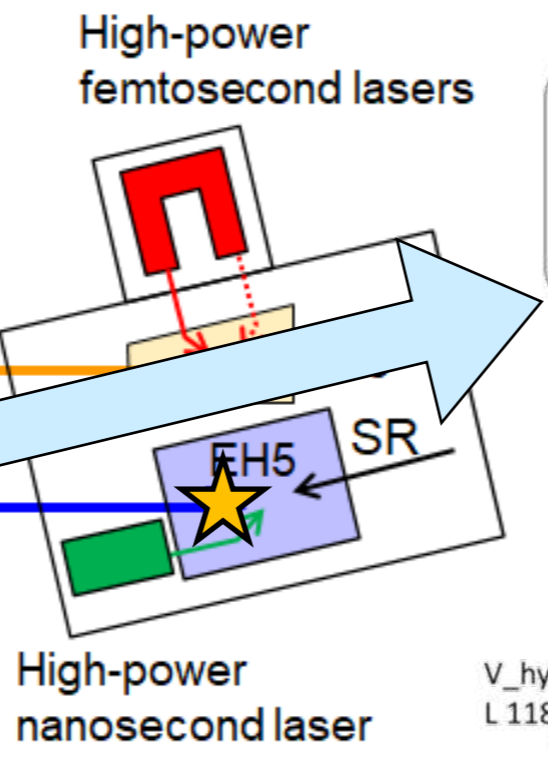


Topics2: sub-10 nm system

SACLA Experimental Facility



★ Nanofocusing system



Sub-10 nm focusing @ 9.1keV

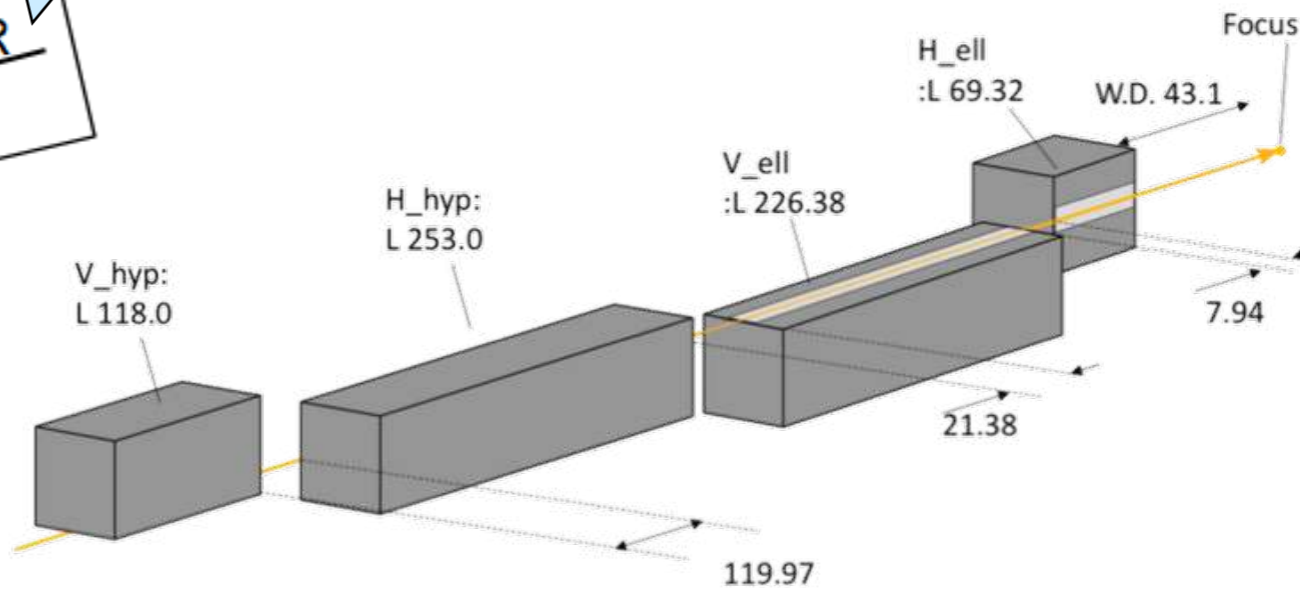
AKB mirrors

Optical interferometer
To monitor XYZ of the focus

Sample unit
 • Sample holder
 • Grating
 • Sample scanner

User's space
 • MPCCDs
 • Spectrometer
 • Any instruments

X-ray S-GI

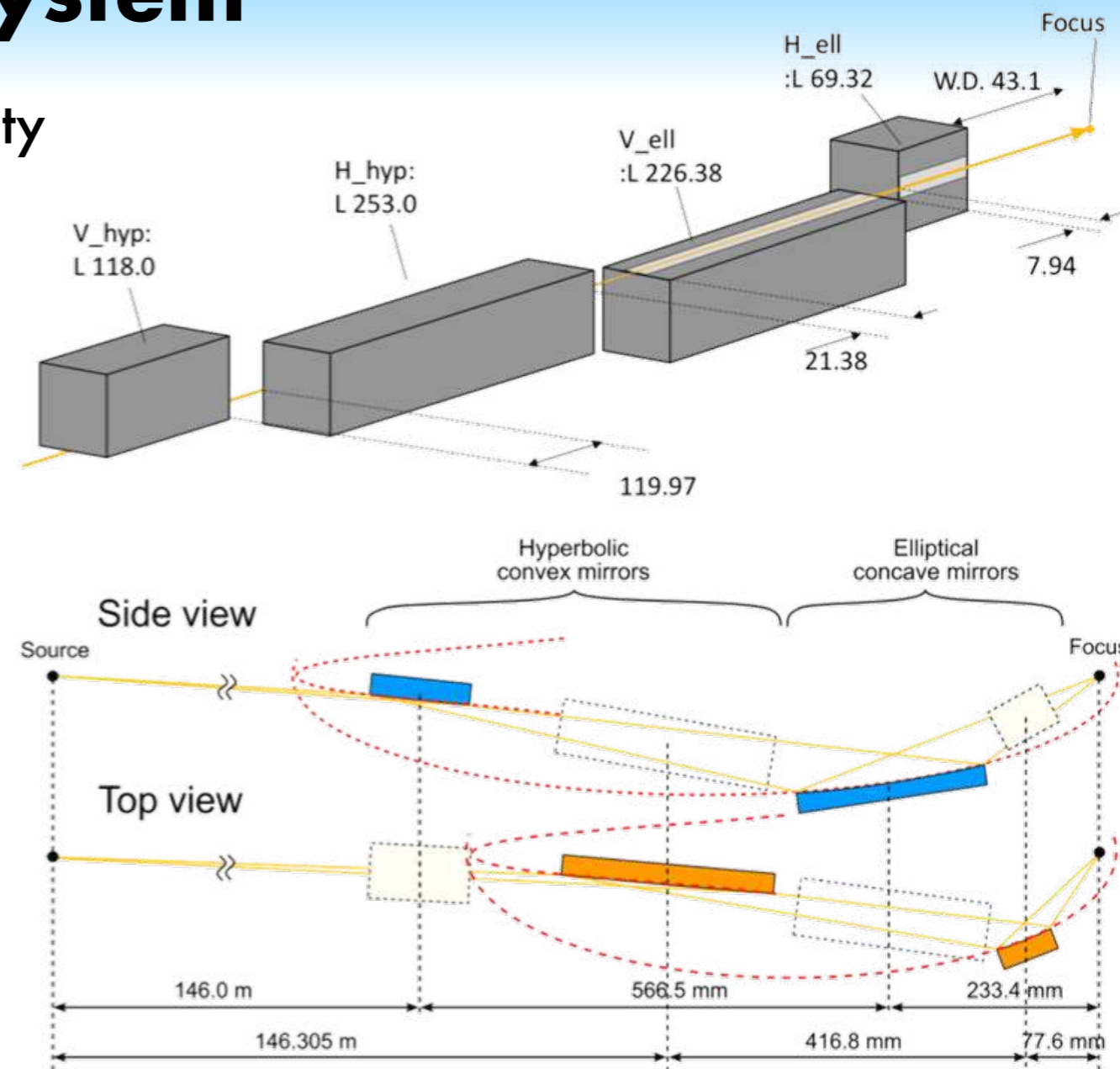


Sub-10 nm focusing system

XFEL 7 nm focusing with 10^{22} W/cm² intensity

Specification

Photon energy :	9.124 keV (w/ multilayer b.w. 200eV)
Reflectivity:	39.6 %
Acceptance:	~500 x 500 μ m (cf. incident ~380 μ m fwhm)
Throughput:	>15% (including all BL-optics)
Sample type:	Solid
Focus size:	6.6 nm x 7.1 nm
Depth of focus:	2 μ m
Tuning time:	currently ~12 hours (initial tuning) ~10 min by grating (re-focusing)
Lifetime of focus:	>10 hours

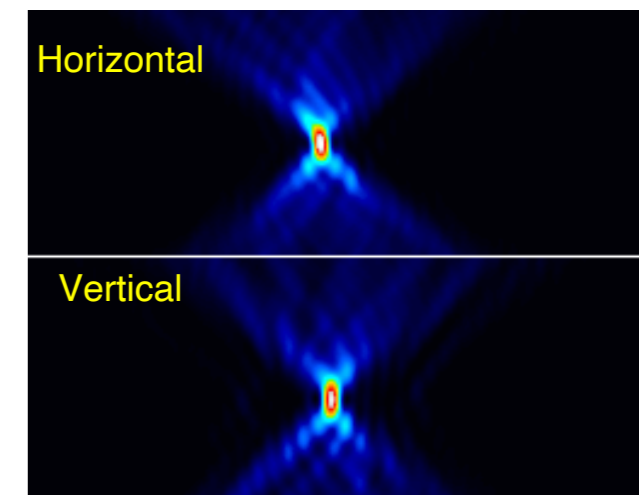
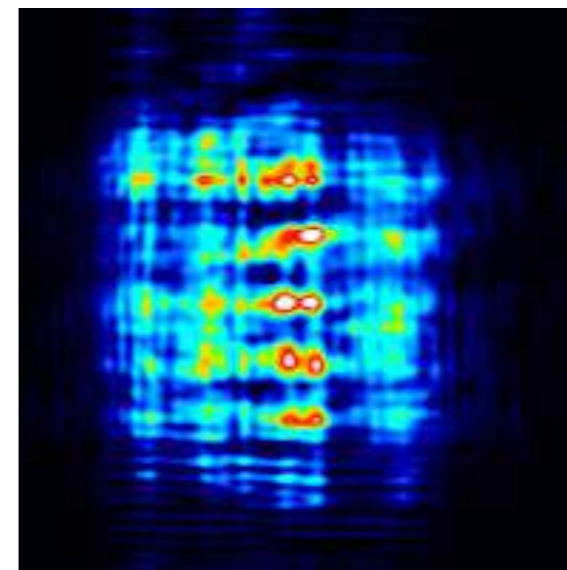


Issues & question

Is the focus truly sub-10 nm?

How to manage the narrow DoF of 2 μ m?

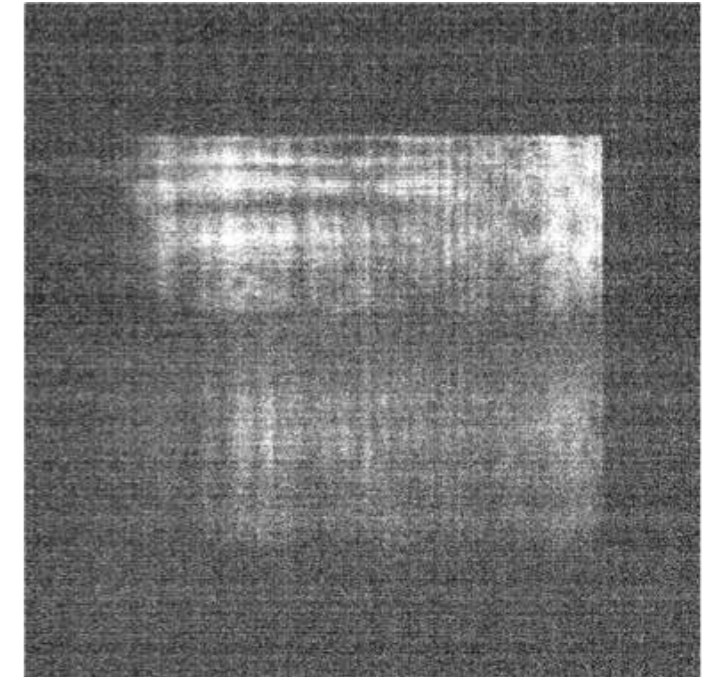
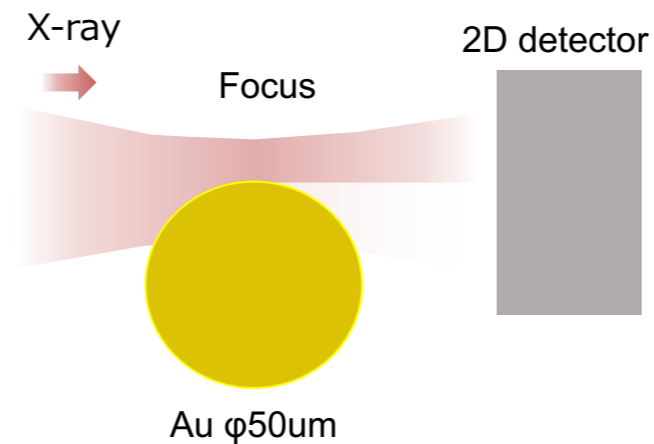
What science will open up?



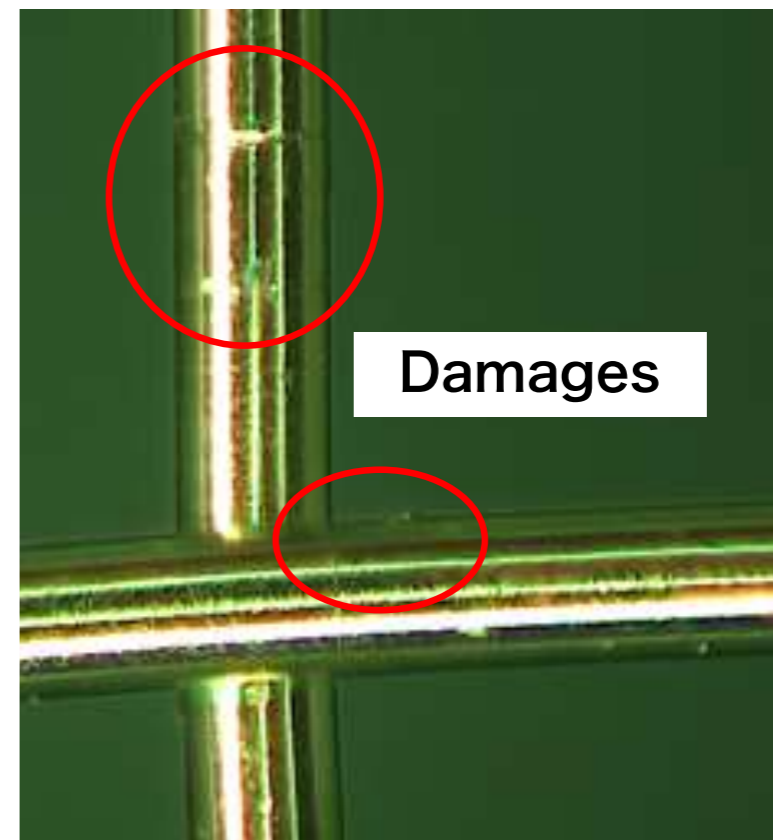
Focus characterization of sub-10 nm XFEL

For the sub-10 nm XFEL beam, wire-scanning method is not realistic.

☑ Focus & samples vibration of ~ 20 nm



☑ sub-10 nm XFELs damage the wire



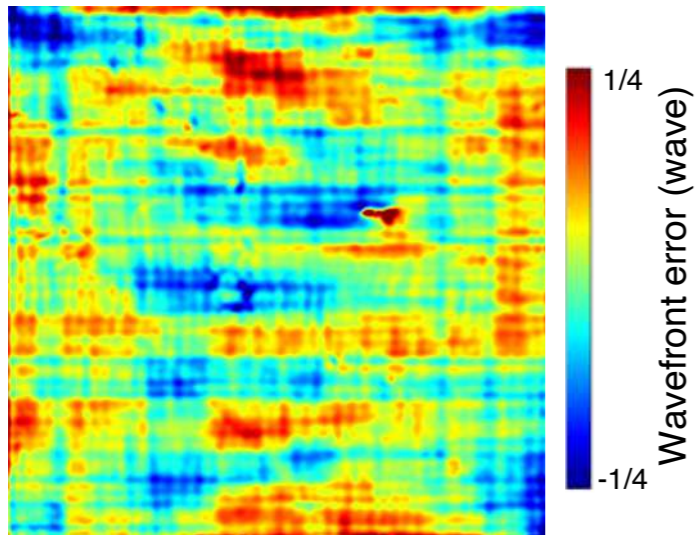
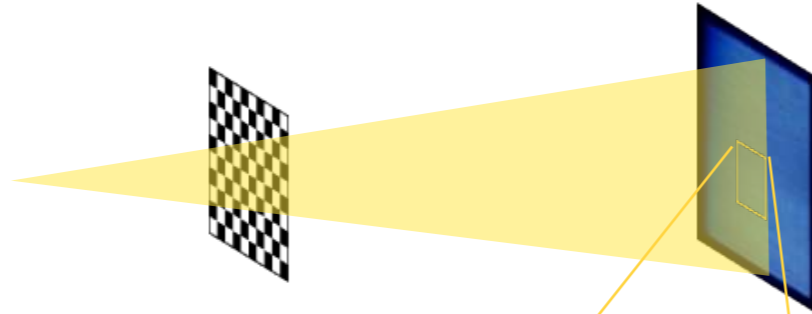


Focus characterization of sub-10 nm XFEL

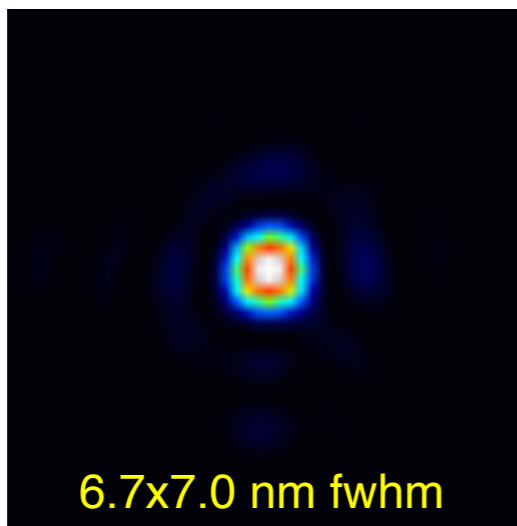
Wavefront measurement by grating interferometer

(75 shot-average)

3um-pitch grating
Camera-length 0.45m
Focus-grating 8.4 mm



Wavefront error

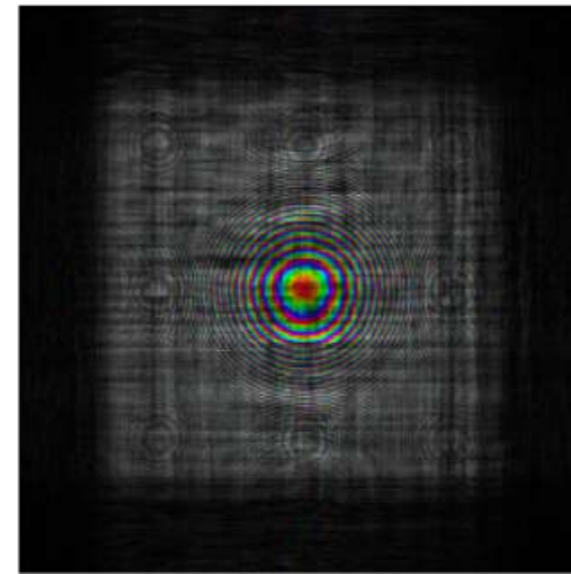
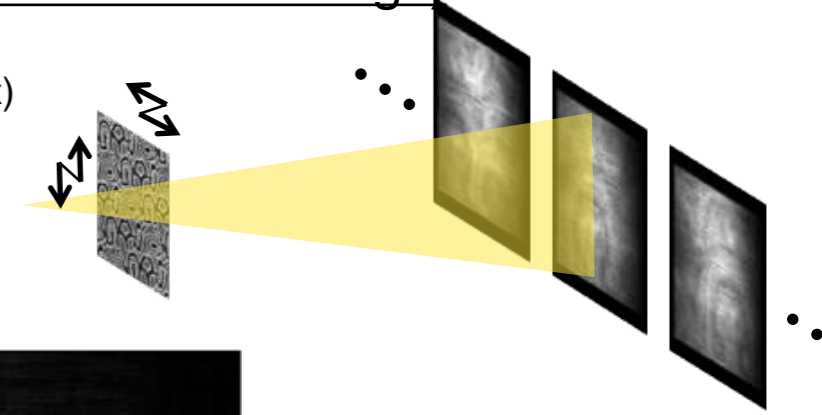


6.7x7.0 nm fwhm

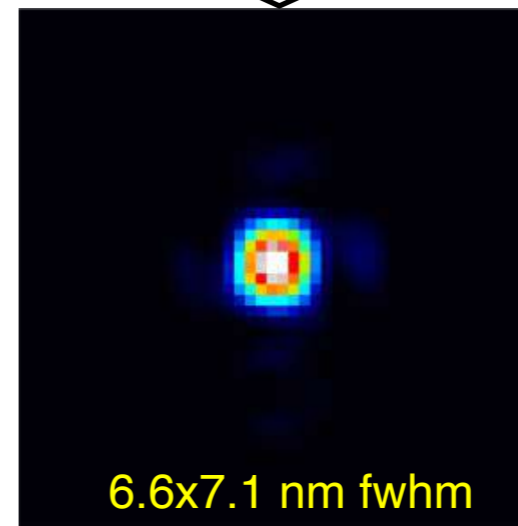
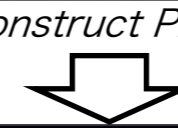
Ptychographic probe measurement

(~25 kshot-average)

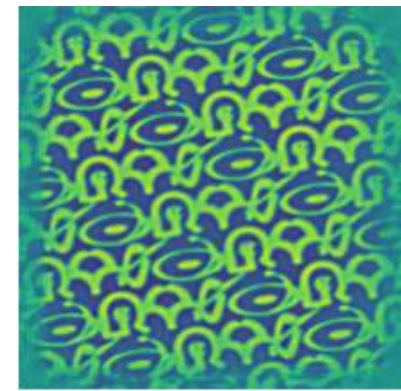
Sample: FIB etched pattern
Detector: MPCCD (50um/pix)
Camera length: 1.14 m
272nm step, 16 x 16 scan
120 um defocus
Attenuated w/ Si t0.8 mm
100 shots/position



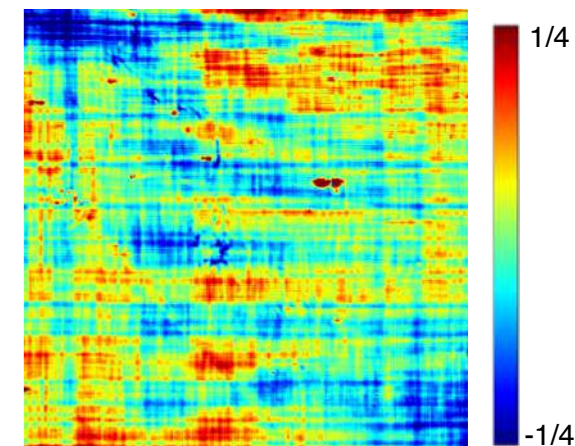
Reconstruct Probe



6.6x7.1 nm fwhm



Reconstruct Object



s-GI & ptycho. consistently indicated 7nm focus size

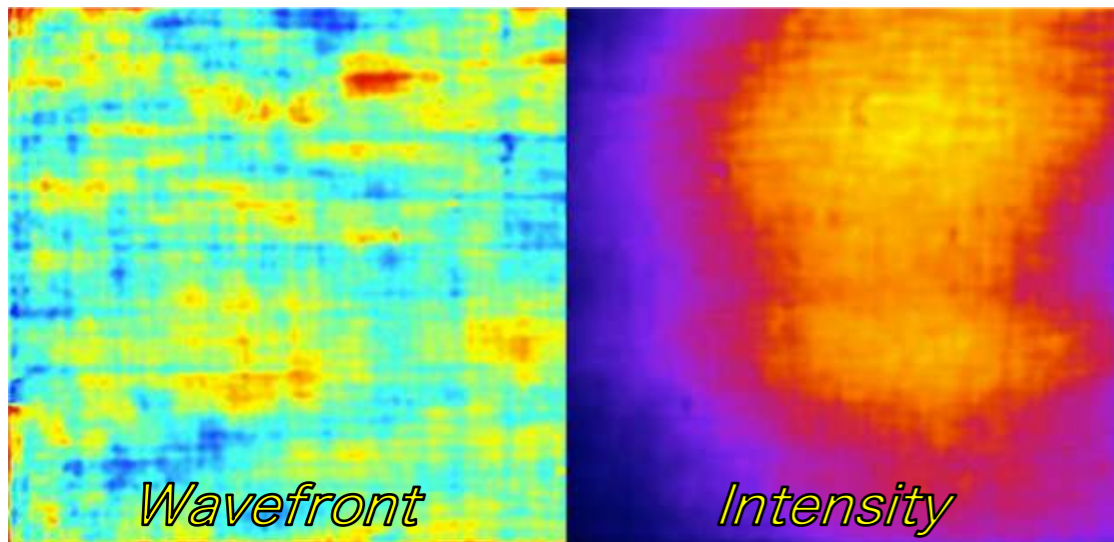
Pulse-to-pulse focus characterization

Single-shot wavefront measurement



30Hz image acquisition
by IMPERX-CMOS

courtesy of SACLA Eng. team



Wavefront

Intensity

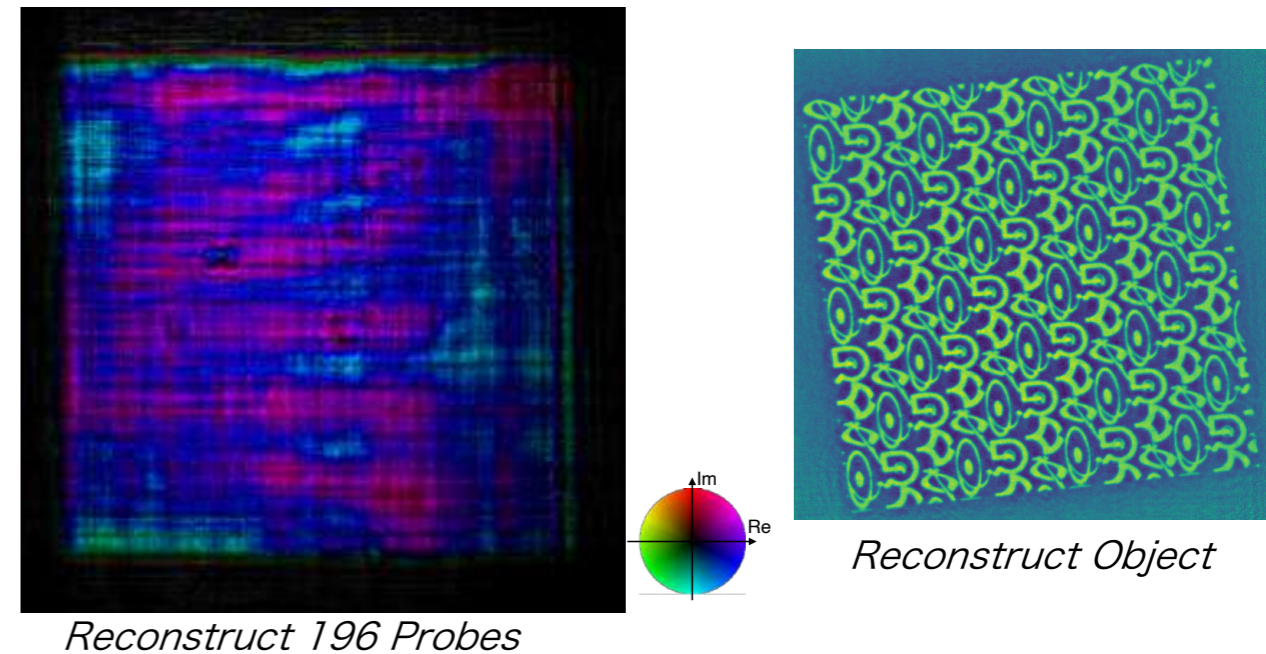
**Single-shot characterization
revealed almost stable wavefronts**

Near-field ptycho. w/ orthogonal probe relaxation

OPR: Orthogonal probe relaxation

↳ individual probes for each of diffraction
can be reconstructed

M. Odstrcil *et al.*, Opt. Express (2016).
S. Sala *et al.*, J. Appl. Cryst. (2020).

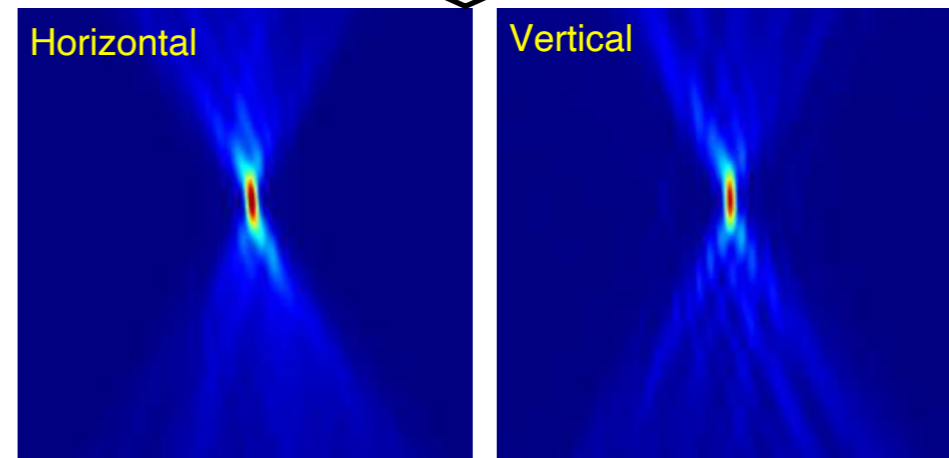


Reconstruct 196 Probes

Reconstruct Object

Horizontal

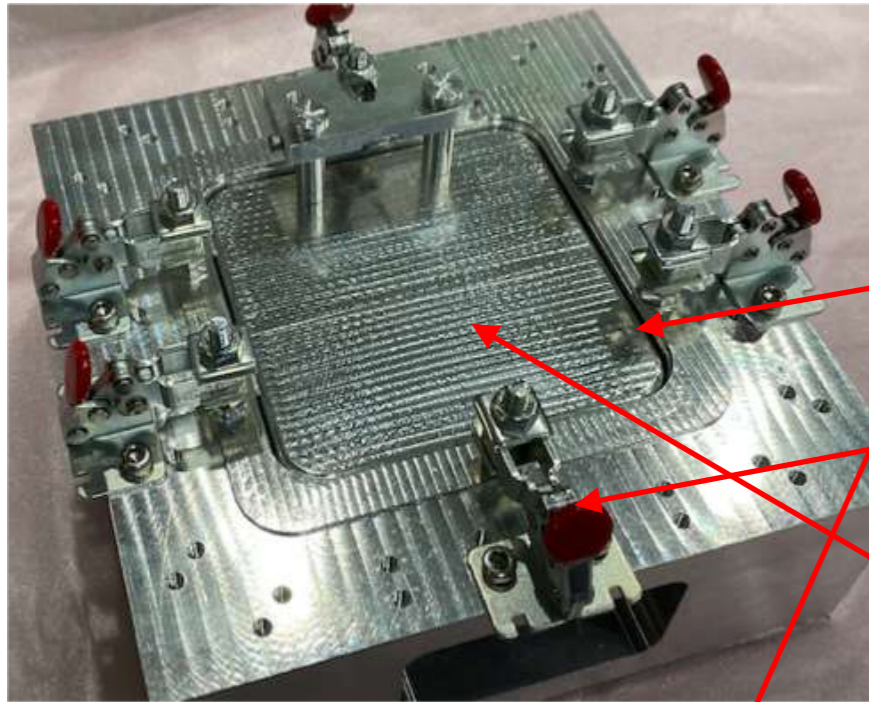
Vertical



How to manage the narrow DoF of 2 μ m

☑ The sample should be placed within a depth of focus of 2 μ m

-> Sample tuner to tighten the film

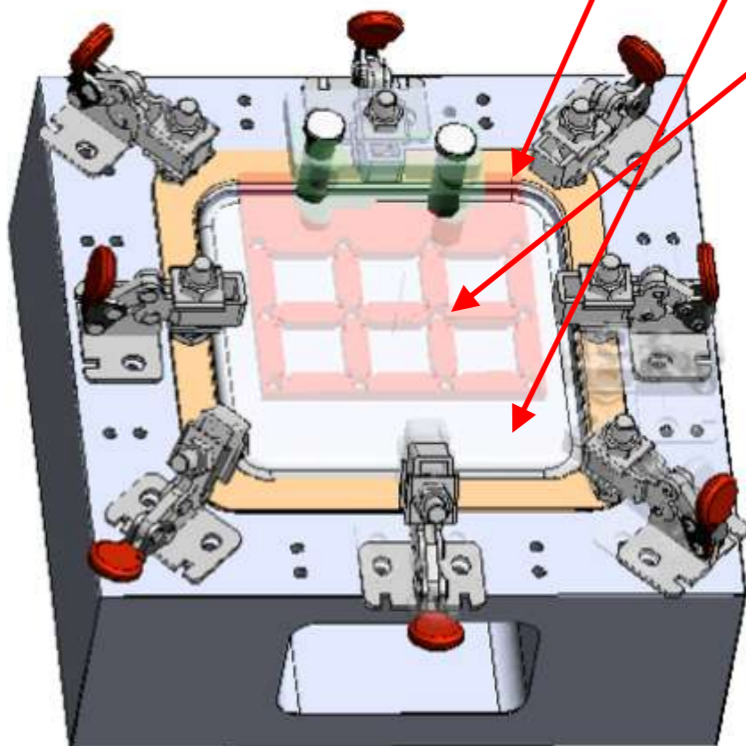


① Set a film

② clamp&hold

③ Raise center stage
& apply tension

④ Put the holder
& glue the film

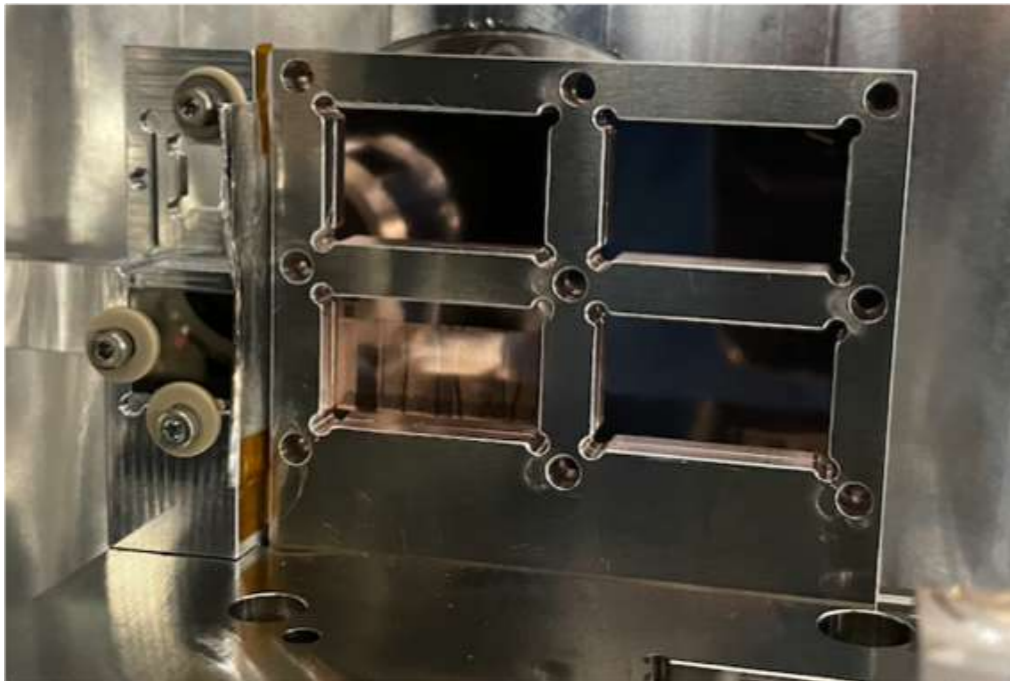
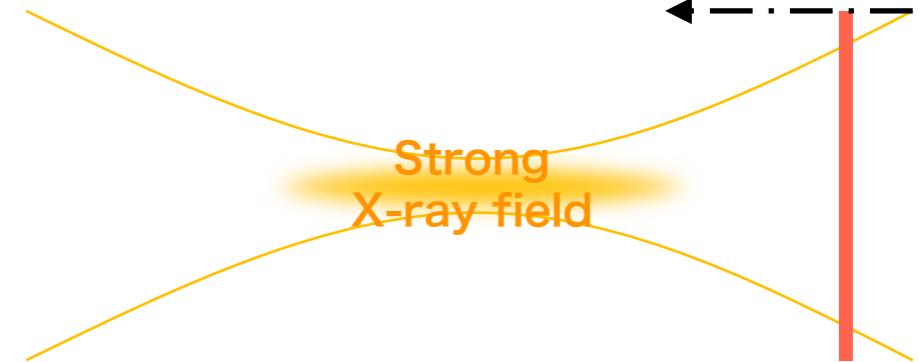


Example of tightened film

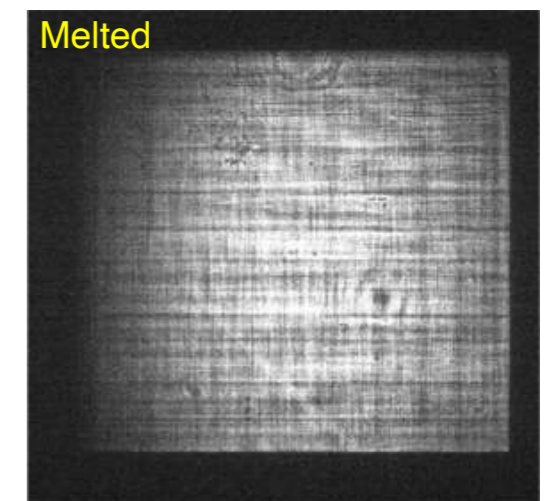
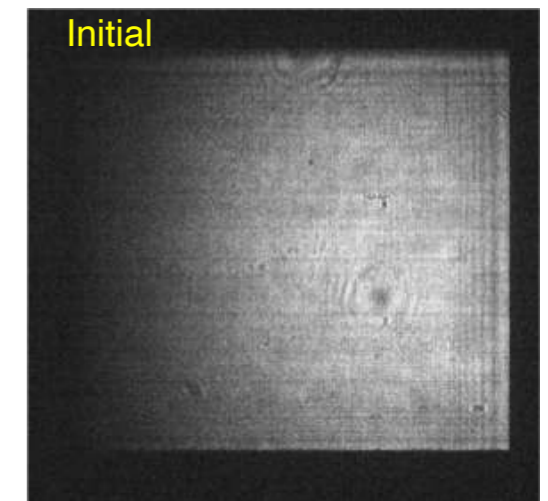
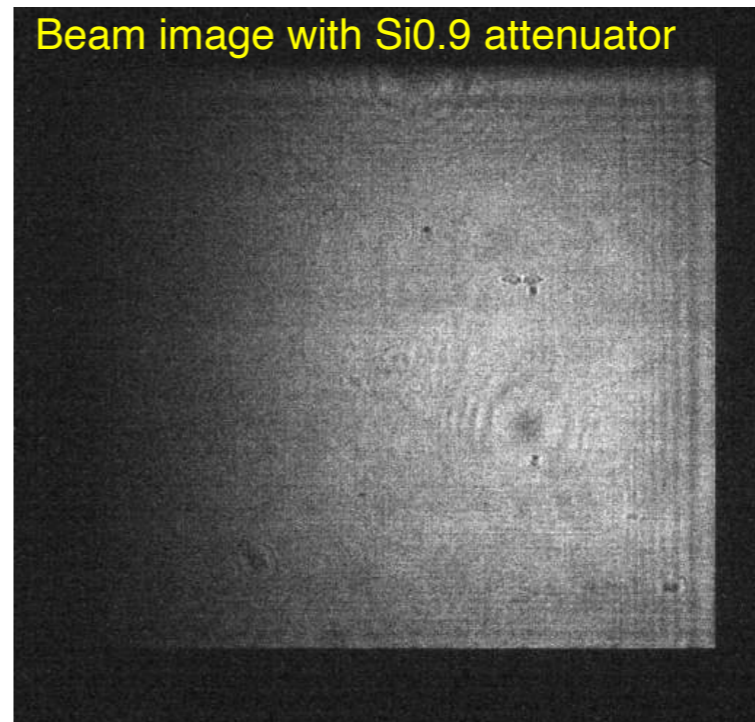
How to manage the narrow DoF of 2 μ m

- ✓ The sample should be placed within a depth of focus of 2 μ m
- > Find the focus position along the optical axis

Scan the sample



Set the prepared sample to the scan stages

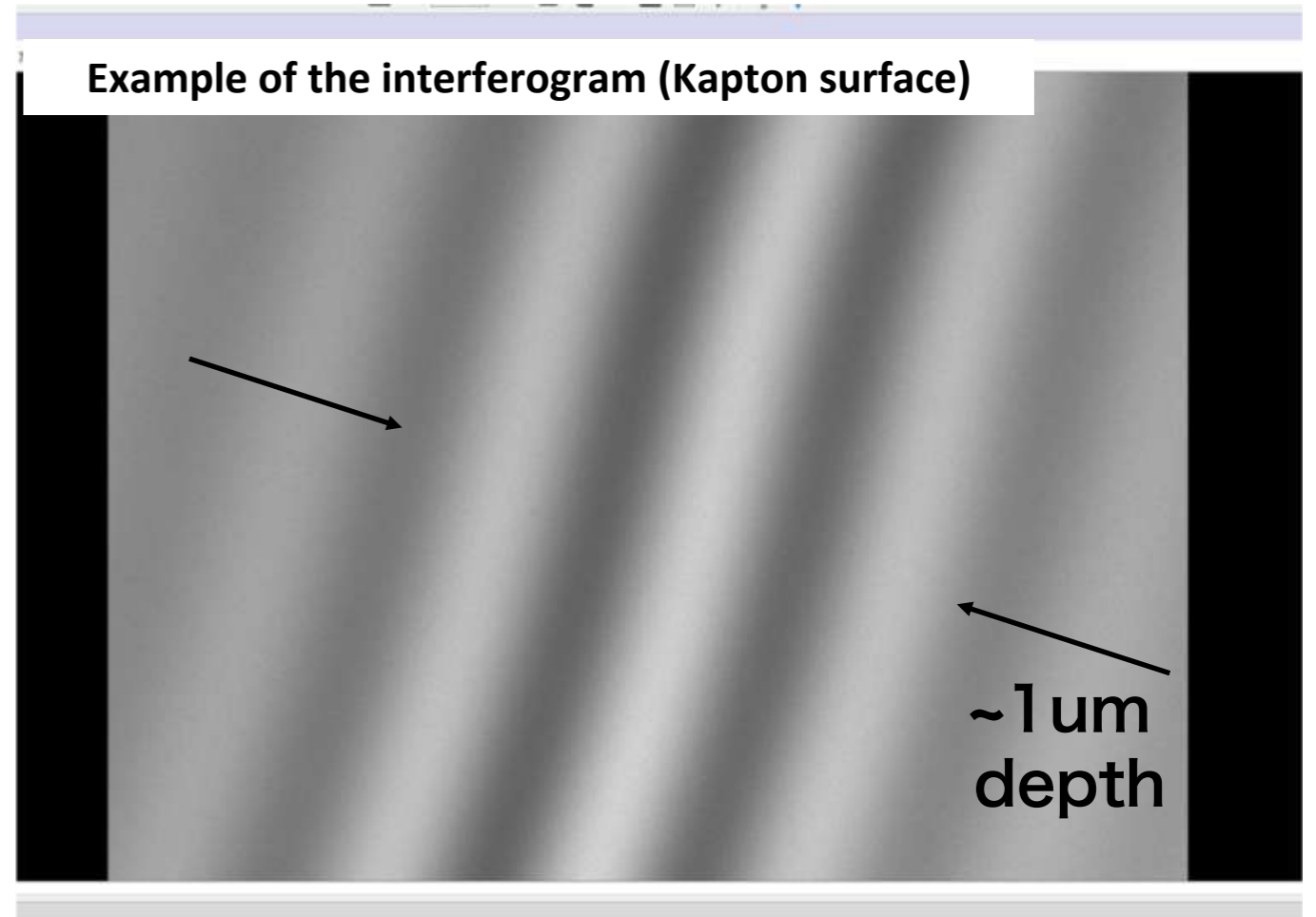
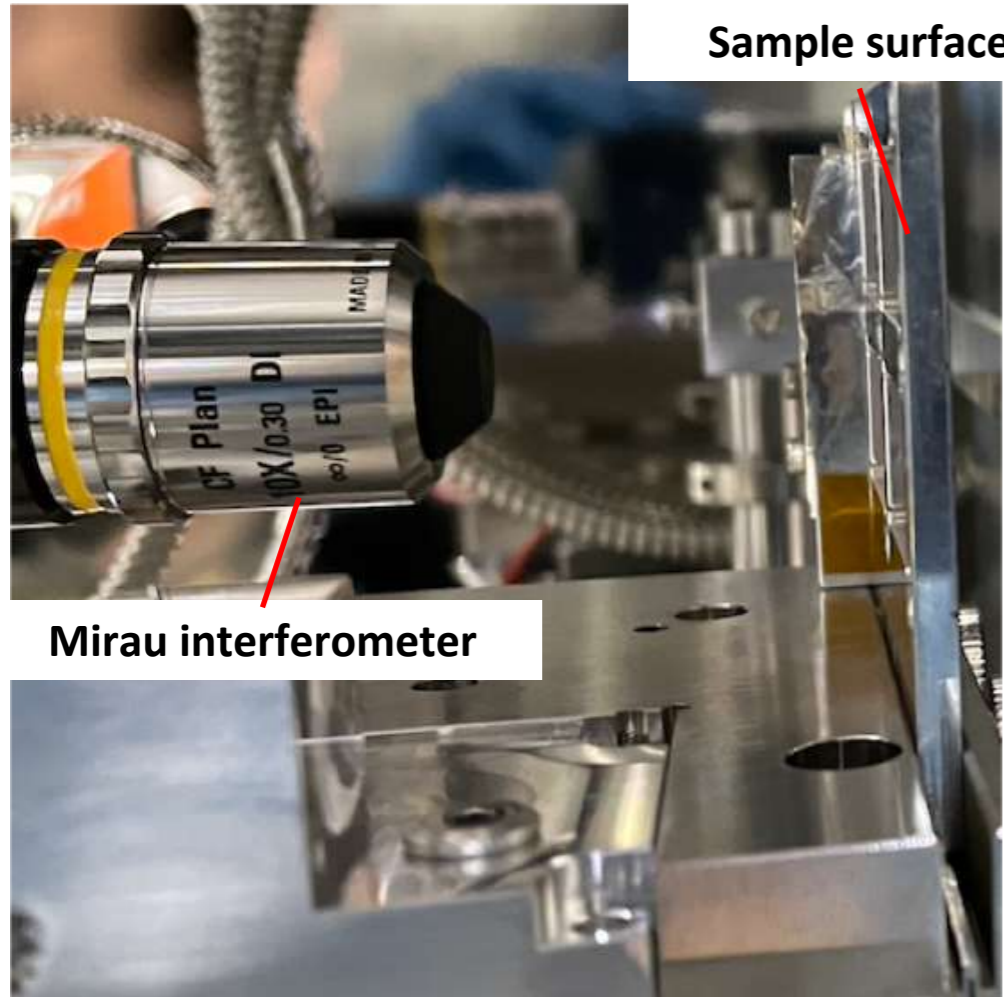


Search the '**melting position**' from upstream/downstream side
Center of the melting position should be the focus

How to manage the narrow DoF of 2 μ m

✓ The sample should be placed within a depth of focus of 2 μ m

-> Tune the sample rotation using sample monitor (optical interferometer)



The sample (tightened film) surface can be kept at the same position within 1~2 μ m.



Targets of the sub-10nm XFEL

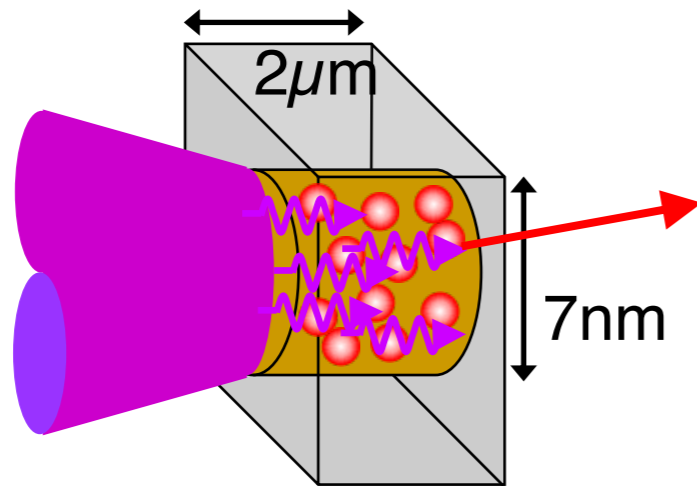
Expected Intensity/fluence

Pulse energy on mirrors : 255 μ J

$$255\mu\text{J} \times 40\%_{\text{reflectivity}} \times 47\%_{\text{Power in fwhm}} / 7 \times 7 \text{nm}^2 / 7\text{fs} \approx \mathbf{1.21 \times 10^{22} \text{ W/cm}^2}$$

$$3.27 \times 10^{10} \text{ photons/shot} \Rightarrow \mathbf{5.83 \times 10^{22} \text{ photons/cm}^2}$$

However,,,

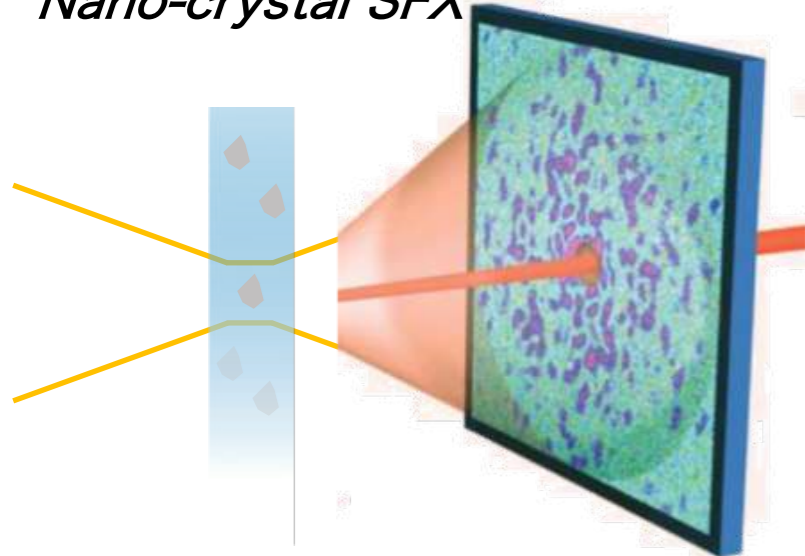


Number of atoms (Cu) in the focus: $\sim 8.3 \times 10^6$

~1000 times less than photons
-> signals should be weak

Targets of the sub-10 nm XFEL (tentative)

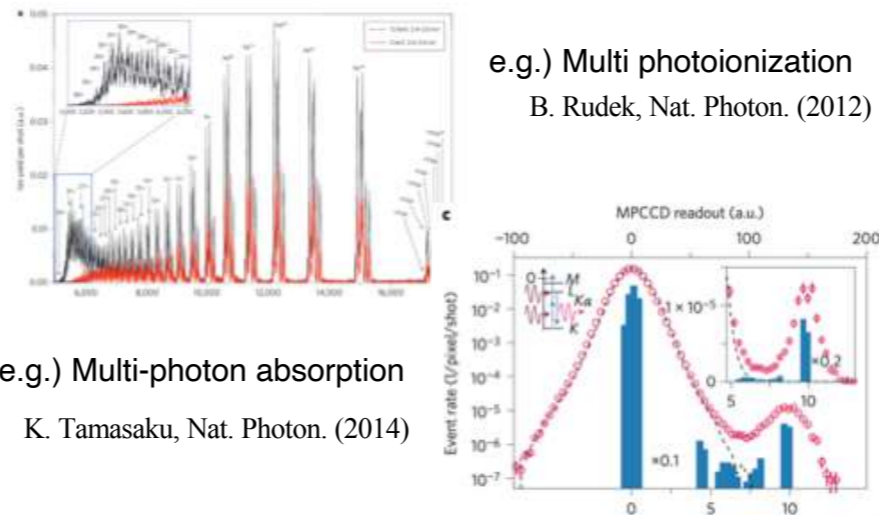
✓ *Nano-crystal SFX*



Shoot smaller samples w/ high flux
 → **single-molecular imaging**

K. J. Gaffney & H. N. Chapman Science. (2007)

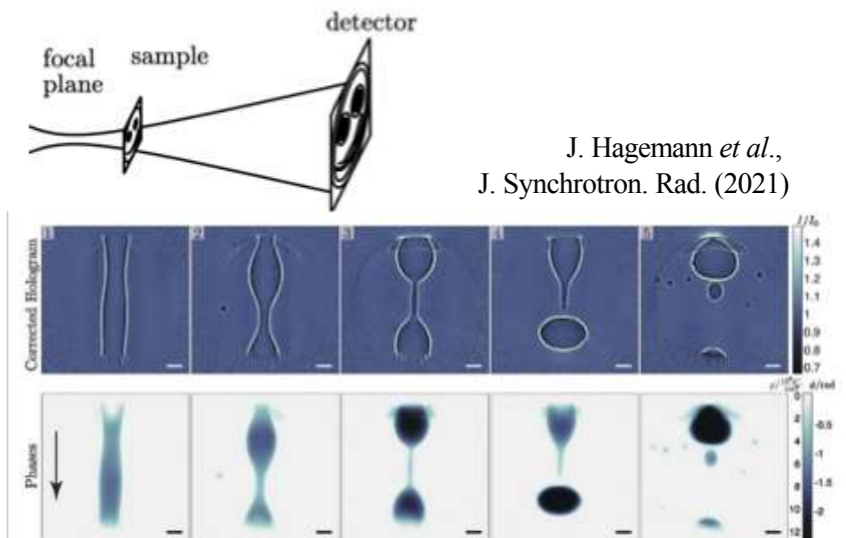
✓ *Nonlinear interaction*



$$\text{Signals} \propto \sigma \cdot I^{2\sim 3}$$

New phenomena of X-ray nonlinear optics

✓ *Nano-resolution phase imaging*



J. Hagemann *et al.*,
 J. Synchrotron. Rad. (2021)

7-nm resolution
 single-shot phase imaging

Topics2: sub-10 nm system

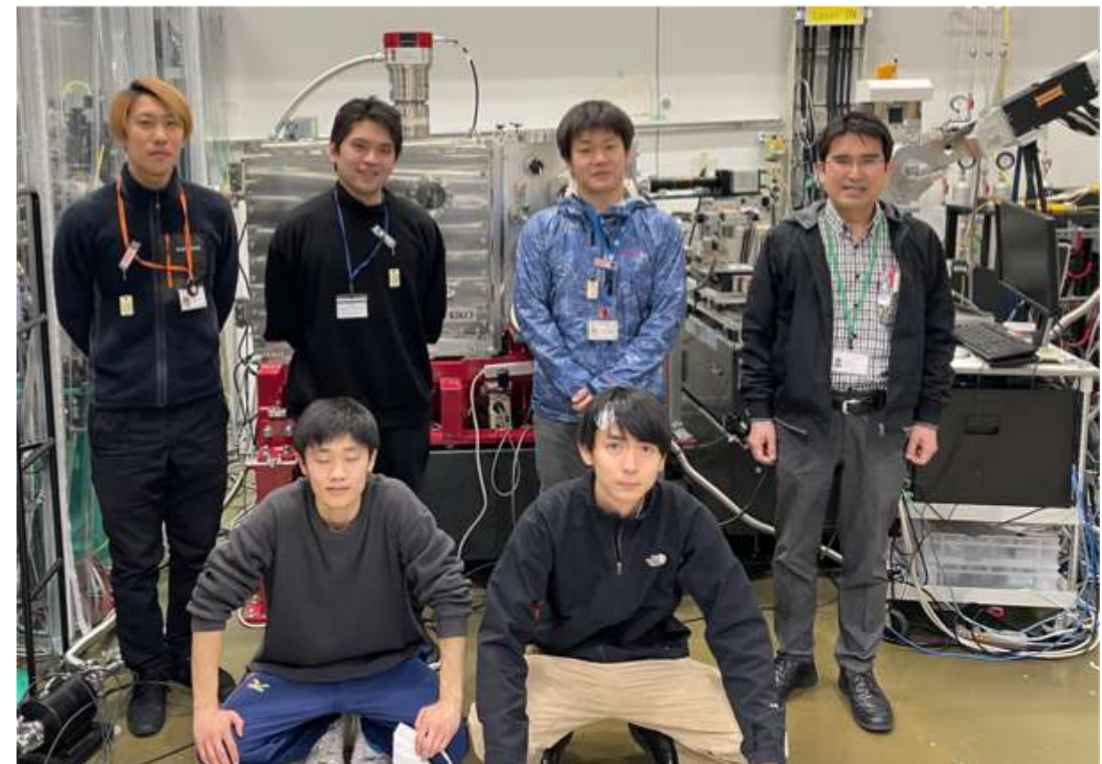
From SACLA side:

7x7 nm focusing system has been developed.

In solid sample case, 2- μ m depth-of-focus is sufficient for practical use.

We believe that the sub-10 XFEL will open up unique & new science

On behalf of the XFEL sub-10nm developing teams (Osaka U., JASRI, RIKEN)



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